



Search Report

EIC 1700

STIC Database Tracking Number: 236558

To: MICHAEL BERNSHTEYN
Location: REM-10D25
Art Unit: 1713
Tuesday, September 18, 2007

Case Serial Number: 10/537120

From: USHA SHRESTHA
Location: EIC1700
REM-4B28 / REM-4B31
Phone: (571)272-3519

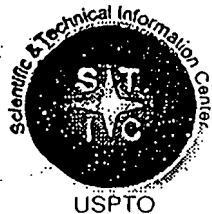
usha.shrestha@uspto.gov

Search Notes

Examiner BERNSHTEYN:

Please see the search results, feel free to contact me if you have any questions or if you like to refine the search query. Thank you for using STIC services!

Regards,
Usha



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher* or *contact:*

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

➤ I am an examiner in Workgroup: Example: 1713

➤ Relevant prior art found, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art not found:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28

SCIENTIFIC REFERENCE
Sci & Tech Inf. Ctr.
SEP 06 REC'D
Pat. & T.M. Office

Access DB# 236558

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: MICHAEL BERNSTEIN Examiner #: 81515 Date: 09/05/07
Art Unit: 1713 Phone Number 30 272-2411 Serial Number: 10/537, 120
Mail Box and Bldg/Room Location: Room 100.25 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Unsaturated carboxylic acid hemiacetal ester, polymers

Inventors (please provide full names): Hiroshi Koyama, Keizo Inoue,
Takahiro Inahama, Mari Sumida

Earliest Priority Filing Date: 02/04/2004

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please, try to find a compound of formula (1) with all the limitations of claims 1 and 2, a process of producing the ester of formula (5) according claim 3, and a polymeric compound of formula (I) with the limitations of claims 4-6.

Thank you

M. Bernstein

10/537120

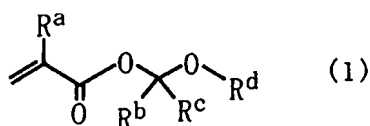
Application No.: Not Yet Assigned

Docket No.: 3273-0203PUS1

JC17 Rec'd PCT/PTO 03 JUN 2005

AMENDMENTS TO THE CLAIMS

Claim 1 (original): An unsaturated carboxylic acid hemiacetal ester represented by the following formula (1);

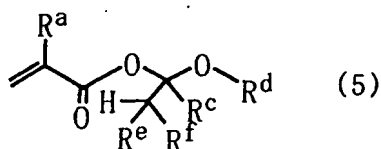


wherein

R^a is a hydrogen atom, a halogen atom, an alkyl group of carbon number 1 to 6 or a haloalkyl group of carbon number 1 to 6, R^b is a hydrocarbon group having a hydrogen atom at a first position, R^c is a hydrogen atom or a hydrocarbon group and R^d is an organic group having a cyclic skeleton.

Claim 2 (original): An unsaturated carboxylic acid hemiacetal ester according to Claim 1, wherein a cyclic skeleton in R^d is a lactone skeleton or a non-aromatic polycyclic skeleton.

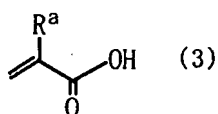
Claim 3 (original): A process of producing an unsaturated carboxylic acid hemiacetal ester, wherein the unsaturated carboxylic acid hemiacetal ester represented by the following formula (5);



wherein

R^a is a hydrogen atom, a halogen atom, an alkyl group of carbon number 1 to 6 or a haloalkyl

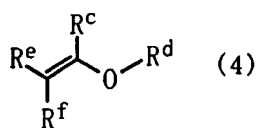
group of carbon number 1 to 6, R^c is a hydrogen atom or a hydrocarbon group, R^d is an organic group having a cyclic skeleton and each of R^e and R^f is a hydrogen atom or a hydrocarbon group; is obtained by allowing an unsaturated carboxylic acid represented by the following formula (3);



wherein

R^a is a hydrogen atom, a halogen atom, an alkyl group of carbon number 1 to 6 or a haloalkyl group of carbon number 1 to 6;

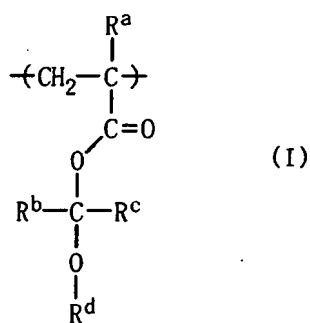
to react with a vinyl ether compound represented by the following formula (4);



wherein

R^c is a hydrogen atom or a hydrocarbon group, R^d is an organic group having a cyclic skeleton and each of R^e and R^f is a hydrogen atom or a hydrocarbon group.

Claim 4 (original): A polymeric compound having a repeated unit represented by the formula (I);



wherein R^a is a hydrogen atom, a halogen atom, an alkyl group of carbon number 1 to 6 or a haloalkyl group of carbon number 1 to 6, R^b is a hydrocarbon group having a hydrogen atom at a first position, R^c is a hydrogen atom or a hydrocarbon group and R^d is an organic group having a cyclic skeleton.

Claim 5 (original): A polymeric compound according to Claim 4, further having a repeated unit corresponding to at least one monomer selected from a monomer having a lactone skeleton, a monomer having a cyclic ketone skeleton, a monomer having an acid anhydride group and a monomer having an imide group; provided that except for a repeated unit represented by the formula (I).

Claim 6 (original): A polymeric compound according to Claim 4 or Claim 5, further having a repeated unit corresponding to at least one monomer selected from a monomer having a hydroxyl group, a monomer having a mercapto group and a monomer having a carboxyl group.

Claim 7 (currently amended): A photoresist resin composition containing at least a polymeric compound described in ~~any one of Claim 4 to Claim 6~~ Claim 4 and a photo-acid generator.

Claim 8 (original): A process of producing a semi-conductor comprising

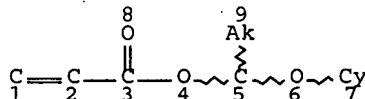
Application No.: Not Yet Assigned

Docket No.: 3273-0203PUS1

steps of coating a photoresist resin composition described in Claim 7 on a base or substrate to form a resist film and forming a pattern through exposure and development.

=> d que 19

L3 STR



NODE ATTRIBUTES:
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 9

STEREO ATTRIBUTES: NONE

L5 105 SEA FILE=REGISTRY SSS FUL L3
 L7 70 SEA FILE=HCAPLUS ABB=ON PLU=ON L5
 L8 63 SEA FILE=HCAPLUS ABB=ON PLU=ON L7 AND (1840-2004)/PRY,AY,
 PY
 L9 48 SEA FILE=HCAPLUS ABB=ON PLU=ON L8 AND PREP/RL

=> d 19 1-48 ibib ed abs hitstr hitind

L9 ANSWER 1 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:982616 HCAPLUS Full-text

DOCUMENT NUMBER: 145:366502

TITLE: Composition for forming lower layer film for
 lithography comprising compound having protected
 carboxyl group

INVENTOR(S): Takei, Satoshi; Kishioka, Takahiro; Sakaida,
 Yasushi; Shinjo, Tetsuya

PATENT ASSIGNEE(S): Nissan Chemical Industries, Ltd., Japan

SOURCE: U.S. Pat. Appl. Publ., 26pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2006210915	A1	20060921	US 2006-565968	20060131
US 7226721	B2	20070605		
PRIORITY APPLN. INFO.:			JP 2003-282738	A 20030730
			JP 2003-345476	A 20031003
			WO 2004-JP10939	W 20040730

ED Entered STN: 22 Sep 2006

AB There is provided an underlayer coating forming composition for lithog., and an underlayer coating having a high dry-etching rate compared with photoresist, and causing no intermixing with the photoresist, which are used in lithog. process of manufacture of semiconductor device. Concretely it is an underlayer coating forming composition comprising a compound having a protected carboxyl group, a compound having a group capable of reacting with a carboxyl group and a solvent, and an underlayer coating forming composition comprising a compound having a group capable of reacting with a carboxyl group and a protected carboxyl group and a solvent.

IT 910305-15-6P

(composition for forming lower layer film for lithog. containing)

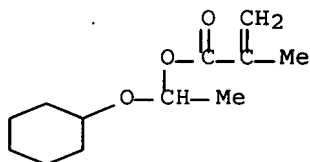
RN 910305-15-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

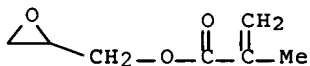
CMF C12 H20 O3



CM 2

CRN 106-91-2

CMF C7 H10 O3



INCL 430270100

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 38

IT 682744-69-0P 890015-04-0P 910305-15-6P 910305-16-7P

910305-17-8P 910305-18-9P 910305-19-0P

(composition for forming lower layer film for lithog. containing)

REFERENCE COUNT: 20 THERE ARE 20 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L9 ANSWER 2 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:492637 HCAPLUS Full-text
 DOCUMENT NUMBER: 144:477832

BERNSHTEYN 10/537,120

TITLE: Preparation of photopolymers having high sensitivity to deep UV or electron beams for resists

INVENTOR(S): Momose, Akira; Mihashi, Takashi; Otake, Atsushi; Ueda, Shoji

PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 65 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006131739	A	20060525	JP 2004-321906	20041105

PRIORITY APPLN. INFO.: JP 2004-321906 20041105

ED Entered STN: 26 May 2006

AB The polymers having unit $[H_2CCR_{11}[Z[OCHA(OR_{14})]n]]$ ($R_{11} = H, Me$; $Z =$ single bond, alkane-derived 2-to-4-valent group, C4-20 alicyclic hydrocarbylene, etc.; $n = 1-3$; $A = Me$; $R_{14} =$ C4-20 monovalent alicyclic hydrocarbyl, C1-5 alkyl), are prepared by solution polymerization and (re)precipitated from organic solvents chosen from (halo)hydrocarbons, nitro compds., nitriles, ethers, ketones, esters, and/or carbonates. Resists containing the polymers are pasted on substrates, exposed to ≤ 250 -nm light, and wet developed to give fine patterns.

IT 876655-79-7P

(preparation of acid-labile photopolymers through repptn. from prescribed solvents for pos. photoresists)

RN 876655-79-7 HCAPLUS

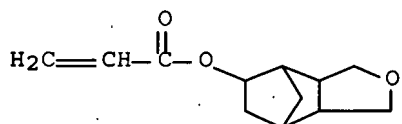
CN 2-Propenoic acid, 2-methyl-, 5(or 6)-cyanobicyclo[2.2.1]hept-2-yl ester, polymer with 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and octahydro-1(or 3)-oxo-4,7-methanoisobenzofuran-5-yl 2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 436852-35-6

CMF C12 H14 O4

CCI IDS

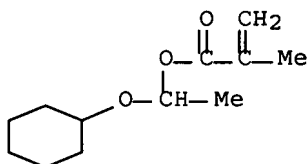


D2=O

CM 2

CRN 143556-62-1

CMF C12 H20 O3

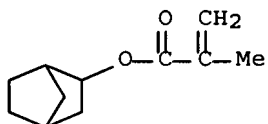


CM 3

CRN 130668-19-8

CMF C12 H15 N O2

CCI IDS



D1-CN

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 37

IT 258879-87-7P 876655-79-7P

(preparation of acid-labile photopolymers through repptn. from prescribed solvents for pos. photoresists)

L9 ANSWER 3 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2006:170173 HCAPLUS Full-text

DOCUMENT NUMBER: 144:243409

TITLE: Polymers for photoresists, their compositions, and excimer laser- or electron beam-photolithography using them for patterns with no defects and good dry etching resistance

INVENTOR(S): Momose, Akira; Otake, Atsushi; Mitsuhashi, Takashi; Ueda, Shoji

PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 74 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006052373	A	20060223	JP 2004-295585	20041008

BERNSHTEYN 10/537,120

PRIORITY APPLN. INFO.:

JP 2004-117113

A 20040412

JP 2004-207487

A 20040714

ED Entered STN: 24 Feb 2006

GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

AB The polymers comprise (A) lactone-containing units I [R41 = H, Me; R401, R402 = H, C1-6 alkyl, OH, CO2H, C1-6 alkyl carboxylate, etc.; X5 = (un)substituted C1-6 alkyl, OH, CO2H, C1-6 acyl, amino, etc.; i = 0, 1; n5 = 0-4; m = 1, 2], II [R42 = same as R41; R201, R202 = C1-6 alkyl, OH, CO2H, C1-6 alkyl carboxylate; A1, A2 = same as R401, R402; X6 = same as X5; n6 = 0-4], etc., (B) units containing acid-dissociable groups III (R31 = H, Me; R1 = C1-3 alkyl; X1 = C1-6 alkyl; n1 = 0-4), CH2CR32[CO2CR321R322(OR323)] (R32 = H, Me; R323 = C4-20 alicyclic, C1-4 alkyl; R321, R322 = H, C1-4 alkyl, etc.), etc., and (C) units containing hydrophilic alicyclic structures IV [R51 = H, Me; R501 = H, C1-3 alkyl; X51 = (un)substituted C1-6 alkyl, C(CF3)2OH, OH, cyano, CO2H, C1-6 acyl, amino, etc.; n51 = 1-4], CH2CR52(CO2CR521R522X52) (R52 = H, Me; R521 = C1-6 alkyl, OH, CO2H, etc.; R522 = C1-6 alkyl, bridged cyclic hydrocarbon group with R521; X52 = same as X51), etc., wherein the polymers are terminated with groups of QB1Y [B1 = (un)substituted C1-20 alkylene (substituent = C1-6 alkyl carboxylate, cyano, amino), cyclic hydrocarbylene; Y = OH, CO2H, SO3H, CONHR1, OSO2NHR1; R1 = C1-6 alkyl, cycloalkyl; Q = direct bond, S, O, NB2; B2 = H, C1-10 alkyl, cycloalkyl].

IT 876655-80-0P

(terminated acrylic telomers for excimer laser or electron-sensitive photoresists for patterns with no defects and good dry etching resistance)

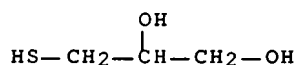
RN 876655-80-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 5(or 6)-cyanobicyclo[2.2.1]hept-2-yl ester, telomer with 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate, 3-mercapto-1,2-propanediol and octahydro-1(or 3)-oxo-4,7-methanoisobenzofuran-5-yl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96-27-5

CMF C3 H8 O2 S



CM 2

CRN 876655-79-7

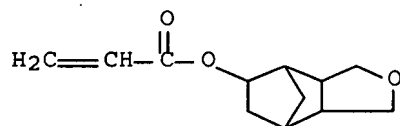
CMF (C12 H20 O3 . C12 H15 N O2 . C12 H14 O4)x

CCI PMS

CM 3

BERNSHTEYN 10/537,120

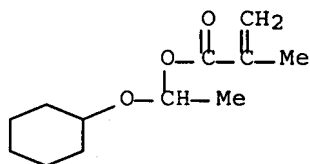
CRN 436852-35-6
CMF C12 H14 O4
CCI IDS



D2=O

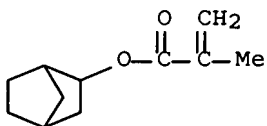
CM 4

CRN 143556-62-1
CMF C12 H20 O3



CM 5

CRN 130668-19-8
CMF C12 H15 N O2
CCI IDS



D1-CN

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT	876655-60-6P	876655-61-7P	876655-63-9P	876655-64-0P
	876655-66-2P	876655-68-4P	876655-70-8P	876655-72-0P
	876655-73-1P	876655-75-3P	876655-76-4P	876655-78-6P

BERNSHTEYN 10/537,120

876655-80-OP 876732-81-9P 876732-85-3P

(terminated acrylic telomers for excimer laser or
electron-sensitive photoresists for patterns with no defects and
good dry etching resistance)

L9 ANSWER 4 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:1003297 HCAPLUS Full-text

DOCUMENT NUMBER: 143:288053

TITLE: Epoxy-containing resin compositions for color
filter protective coatings with good flatness,
transparency, and surface hardness

INVENTOR(S): Baba, Atsushi; Yamazaki, Natsuki; Nishikawa,
Michinori

PATENT ASSIGNEE(S): JSR Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 33 pp..

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005248129	A	20050915	JP 2004-64346	20040308
			<--	
JP 3831947	B2	20061011		
KR 2004081302	A	20040921	KR 2004-15755	20040309
			<--	

PRIORITY APPLN. INFO.: JP 2003-62696 A 20030310

<--
JP 2003-397908 A 20031127

<--
JP 2004-27180 A 20040203

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ED Entered STN: 16 Sep 2005

AB Title compns. comprise (A) polymers with weight average mol. weight ≥ 2000 (GPC measurement based on polystyrene standard) having epoxy structures and ≥ 1 structure selected from carboxylic acid acetal ester structures, carboxylic acid ketal ester structures, and carboxylic acid tert-Bu ester structures and (B) compds. having ≥ 2 epoxy structures excluding A. Thus, styrene 25, 1-(cyclohexyloxy)ethyl methacrylate 20, glycidyl methacrylate 45, and tricyclo[5.2.1.0^{2,6}]decan-8-yl methacrylate were polymerized at 70° to give a copolymer with Mw 20,000 and polydispersity 2.5, 100 parts of which was mixed with Epikote 157S65 10.0, SH 28PA (surfactant) 0.1, γ -glycidoxypropyltrimethoxysilane 15, and benzoyl-2-methyl-4-hydroxyphenylmethylsulfonium hexafluoroantimonate 1 parts, applied on a glass substrate, prebaked at 80° for 5 min, and heat-treated at 230° for 60 min to give a protective coating, showing good heat resistance, transparency, flatness, adhesion, pencil hardness 4H, and dynamic microhardness 29 at 23° and 25 at 140°.

IT 824955-64-8P 824955-65-9P 864376-38-5P

(epoxy-containing resin compns. for color filter protective coatings
with good flatness, transparency, and surface hardness)

RN 824955-64-8 HCAPLUS

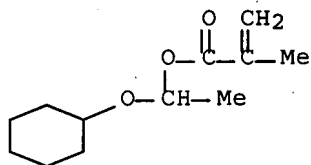
CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer
with Epikote 157S65, ethenylbenzene, octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

BERNSHTEYN 10/537,120

CM 1

CRN 143556-62-1

CMF C12 H20 O3



CM 2

CRN 137598-82-4

CMF Unspecified

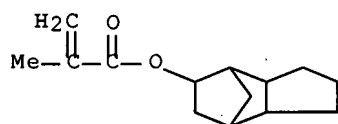
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 34759-34-7

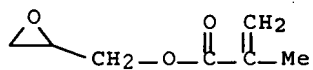
CMF C14 H20 O2



CM 4

CRN 106-91-2

CMF C7 H10 O3



CM 5

CRN 100-42-5

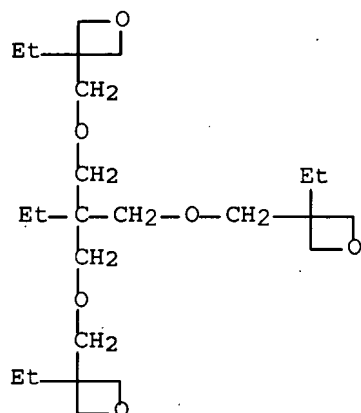
CMF C8 H8

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, 3,3'-[[2-ethyl-2-[[3-ethyl-3-oxetanyl)methoxy)methyl]-1,3-propanediyl]bis(oxymethylene)]bis[3-ethyloxetane], octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 180423-87-4

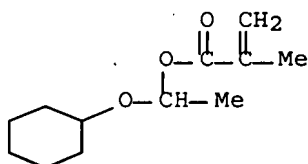
CMF C24 H44 O6



CM 2

CRN 143556-62-1

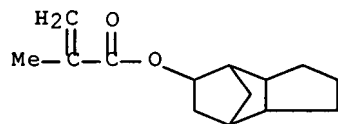
CMF C12 H20 O3



CM 3

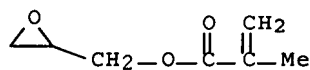
BERNSHTEYN 10/537,120

CRN 34759-34-7
CMF C14 H20 O2



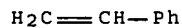
CM 4

CRN 106-91-2
CMF C7 H10 O3



CM 5

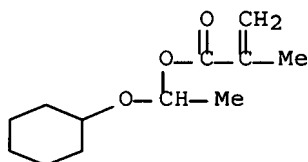
CRN 100-42-5
CMF C8 H8



RN 864376-38-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer
with 1-cyclohexyl-1H-pyrrole-2,5-dione, Epikote 157S65, ethenylbenzene
and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1
CMF C12 H20 O3



CM 2

CRN 137598-82-4

CMF Unspecified

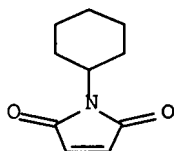
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 1631-25-0

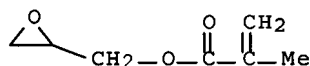
CMF C10 H13 N O2



CM 4

CRN 106-91-2

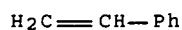
CMF C7 H10 O3



CM 5

CRN 100-42-5

CMF C8 H8



IT 864376-32-9P 864376-34-1P

(intermediate; epoxy-containing resin compns. for color filter protective coatings with good flatness, transparency, and surface hardness)

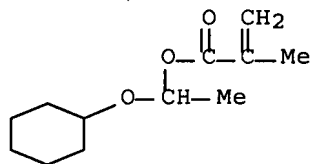
RN 864376-32-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

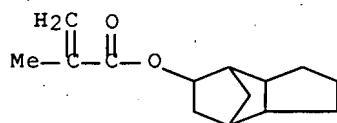
CMF C12 H20 O3



CM 2

CRN 34759-34-7

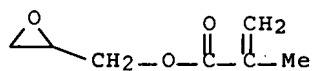
CMF C14 H20 O2



CM 3

CRN 106-91-2

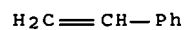
CMF C7 H10 O3



CM 4

CRN 100-42-5

CMF C8 H8



RN 864376-34-1 HCAPLUS

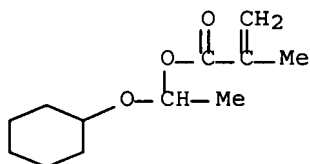
BERNSHTEYN 10/537,120

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer
with 1-cyclohexyl-1H-pyrrole-2,5-dione, ethenylbenzene and
oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

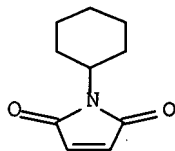
CMF C12 H20 O3



CM 2

CRN 1631-25-0

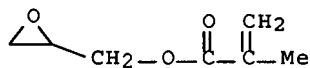
CMF C10 H13 N O2



CM 3

CRN 106-91-2

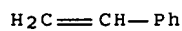
CMF C7 H10 O3



CM 4

CRN 100-42-5

CMF C8 H8



IC ICM C08G059-42
ICS G02F001-1335
CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74
IT 824955-64-8P 824955-65-9P 824955-66-0P,
N-Cyclohexylmaleimide-Epikote 157S65-glycidyl methacrylate-styrene-
tetrahydro-2H-pyran-2-yl methacrylate copolymer 824955-67-1P
864376-38-5P 864376-39-6P 864376-40-9P 864376-41-0P
(epoxy-containing resin compns. for color filter protective coatings
with good flatness, transparency, and surface hardness)
IT 864376-32-9P 864376-33-0P 864376-34-1P
864376-35-2P 864376-36-3P 864376-37-4P
(intermediate; epoxy-containing resin compns. for color filter
protective coatings with good flatness, transparency, and surface
hardness)

L9 ANSWER 5 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2005:823680 HCAPLUS Full-text
DOCUMENT NUMBER: 143:219461
TITLE: Unsaturated carboxylic acid hemiacetal esters and
polymers for resin composition for photoresists
with good acid release
INVENTOR(S): Koyama, Hiroshi; Inoue, Keizo; Iwahama, Takahiro;
Sumida, Mari
PATENT ASSIGNEE(S): Daicel Chemical Industries, Ltd., Japan
SOURCE: PCT Int. Appl., 60 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005075446	A1	20050818	WO 2005-JP794	20050117
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WO 2005075446	A9	20051006		
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RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
JP 2005220059	A	20050818	JP 2004-28595	20040204
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JP 2005248153	A	20050915	JP 2004-303478	20041018
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US 2006160247	A1	20060720	US 2005-537120	20050603
PRIORITY APPLN. INFO.:			JP 2004-28594	A 20040204
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			JP 2004-28595	A 20040204

JP 2004-303478

A 20041018

WO 2005-JP794

W 20050117

OTHER SOURCE(S): MARPAT 143:219461

ED Entered STN: 19 Aug 2005

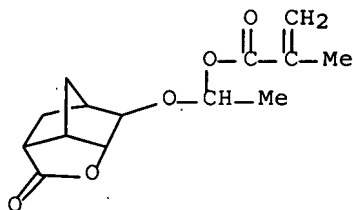
AB Title polymers comprise repeating units $\text{CH}_2\text{:CRACOOCRbRcORD}$, wherein $\text{Ra} = \text{H}$, halogeno, C1-6 alkyl, or C1-6 haloalkyl; $\text{Rb} =$ hydrocarbon group having a hydrogen atom in the 1-position; $\text{Rc} = \text{H}$ or a hydrocarbon group; and $\text{Rd} =$ organic group containing a cyclic skeleton. The polymers may further contain repeating units corresponding to ≥ 1 monomer selected from monomers having a lactone skeleton, monomers having a cyclic ketone skeleton, monomers having an acid anhydride group, and monomers having an imide group (excluding the unsatd. carboxylic acid hemiacetal ester repeating unit and/or monomer selected from monomers having a hydroxy group, etc.). Thus, 0.118 mol 2-vinyloxy-4-oxatricyclo[4.2.1.0^{3,7}]nonan-5-one and 0.59 mol methacrylic acid were reacted at 20° for 6 h in the presence of 0.12 mmol 4-methoxyphenol and 120 mg phosphoric acid to give 2-(1-methacryloyloxyethoxy)-4-oxatricyclo[4.2.1.0^{3,7}]nonan-5-one, 5.41 g of which was polymerized with 4.93 g 1-methacryloyloxy-4-oxatricyclo[4.3.1.1^{3,8}]undecan-5-one and 4.66 g 1-hydroxy-3-methacryloyloxyadamantane in the presence of V 601 (dimethyl-2,2'-azobis(2-methylpropionate)) to give a copolymer with M_w 9800 and polydispersity 1.88, 100 parts of the resulting copolymer was mixed with 10 parts triphenylsulfonium hexafluoroantimonate and propylene glycol monomethyl ether, applied on a silicon wafer, prebaked at 100° for 150 s, irradiated through a photomask, post-baked at 100° for 60 s, developed using 0.3 M an aqueous tetramethylammonium hydroxide soln, showing good pattern.

IT 862474-62-2P 862474-64-4P 862474-66-6P

(monomer; preparation of unsatd. carboxylic acid hemiacetal esters and polymers for resin composition for photoresists with good acid release)

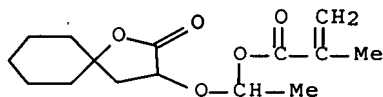
RN 862474-62-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



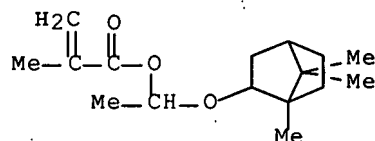
RN 862474-64-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(2-oxo-1-oxaspiro[4.5]dec-3-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



RN 862474-66-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(1,7,7-trimethylbicyclo[2.2.1]hept-2-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



IT 862474-67-7P 862474-68-8P 862474-69-9P

862474-70-2P 862474-71-3P 862474-72-4P

862474-74-6P

(preparation of unsatd. carboxylic acid hemiacetal esters and polymers for resin composition for photoresists with good acid release)

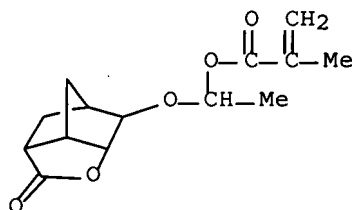
RN 862474-67-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl)oxy]ethyl ester, polymer with 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate and 5-oxo-4-oxatricyclo[4.3.1.1^{3,8}]undec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-62-2

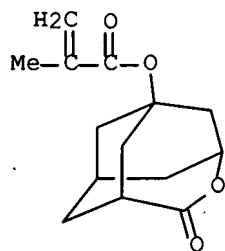
CMF C14 H18 O5



CM 2

CRN 348596-87-2

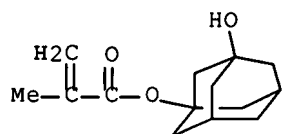
CMF C14 H18 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



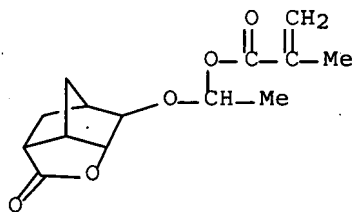
RN 862474-68-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl)oxy]ethyl ester, polymer with 3-hydroxytricyclo[3.3.1.3^{7,7}]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-62-2

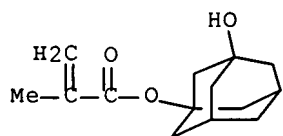
CMF C14 H18 O5



CM 2

CRN 115372-36-6

CMF C14 H20 O3



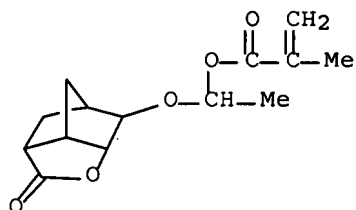
RN 862474-69-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 1-[(hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl)oxy]ethyl 2-methyl-2-propenoate and 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-62-2

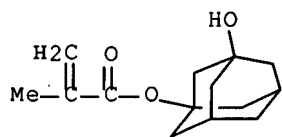
CMF C14 H18 O5



CM 2

CRN 115372-36-6

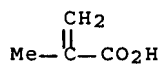
CMF C14 H20 O3



CM 3

CRN 79-41-4

CMF C4 H6 O2



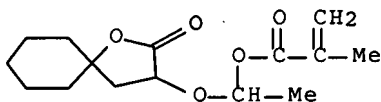
RN 862474-70-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 1-[(2-oxo-1-oxaspiro[4.5]dec-3-yl)oxy]ethyl 2-methyl-2-propenoate and 5-oxo-4-oxatricyclo[4.3.1.1^{3,8}]undec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-64-4

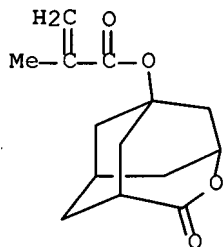
CMF C15 H22 O5



CM 2

CRN 348596-87-2

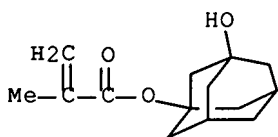
CMF C14 H18 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



RN 862474-71-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl

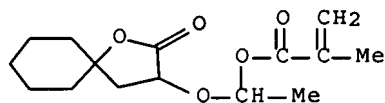
BERNSHTEYN 10/537,120

ester, polymer with 1-[(2-oxo-1-oxaspiro[4.5]dec-3-yl)oxy]ethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-64-4

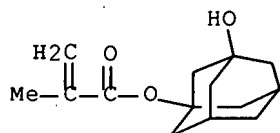
CMF C15 H22 O5



CM 2

CRN 115372-36-6

CMF C14 H20 O3



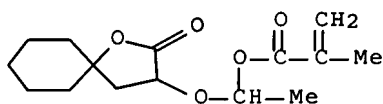
RN 862474-72-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 3-
hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate and
1-[(2-oxo-1-oxaspiro[4.5]dec-3-yl)oxy]ethyl 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

CM 1

CRN 862474-64-4

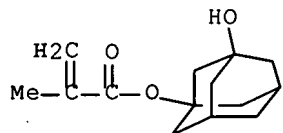
CMF C15 H22 O5



CM 2

CRN 115372-36-6

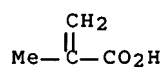
CMF C14 H20 O3



CM 3

CRN 79-41-4

CMF C4 H6 O2



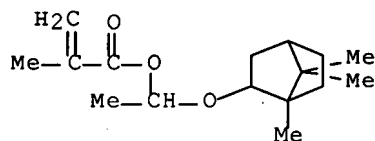
RN 862474-74-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl ester, polymer with 5-oxo-4-oxatricyclo[4.3.1.1.3,8]undec-1-yl 2-methyl-2-propenoate and 1-[(1,7,7-trimethylbicyclo[2.2.1]hept-2-yl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 862474-66-6

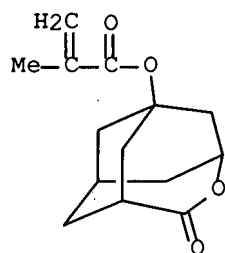
CMF C16 H26 O3



CM 2

CRN 348596-87-2

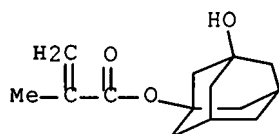
CMF C14 H18 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



IC ICM C07D307-00
ICS C07D307-94; C07C069-54; C08F220-26; G03F007-039; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38, 76
IT 862474-62-2P 862474-64-4P 862474-65-5P
862474-66-6P
(monomer; preparation of unsatd. carboxylic acid hemiacetal esters and polymers for resin composition for photoresists with good acid release)
IT 862474-67-7P 862474-68-8P 862474-69-9P
862474-70-2P 862474-71-3P 862474-72-4P
862474-73-5P 862474-74-6P
(preparation of unsatd. carboxylic acid hemiacetal esters and polymers for resin composition for photoresists with good acid release)
REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L9 ANSWER 6 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2005:813681 HCAPLUS Full-text
DOCUMENT NUMBER: 143:238670
TITLE: Unsaturated carboxylic acid hemiacetal esters, their polymers, photoresist compositions containing them with high sensitivity, and manufacture of semiconductor devices using them
INVENTOR(S): Koyama, Hiroshi; Inoue, Keizo; Iwahama, Takahiro
PATENT ASSIGNEE(S): Daicel Chemical Industries, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese

BERNSHTEYN 10/537,120

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005220059	A	20050818	JP 2004-28595	20040204
WO 2005075446	A1	20050818	WO 2005-JP794	20050117

WO 2005075446 A9 20051006

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.: JP 2004-28594 A 20040204
 JP 2004-28595 A 20040204
 JP 2004-303478 A 20041018

OTHER SOURCE(S): MARPAT 143:238670

ED Entered STN: 18 Aug 2005

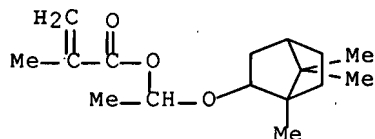
AB The invention relates to hemiacetal unsatd. carboxylates CH₂:C(Ra)CO₂CRbRcORd [Ra = H, halo, C1-6 (halo)alkyl; Rb = hydrocarbyl having H at position 1; Rc = H, hydrocarbyl; Rd = organic groups having cyclic structure].

IT 862474-66-6P

(excimer laser-sensitive photoresists of hemiacetal unsatd. carboxylate polymers for semiconductor devices)

RN 862474-66-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(1,7,7-trimethylbicyclo[2.2.1]hept-2-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



IT 862474-74-6P

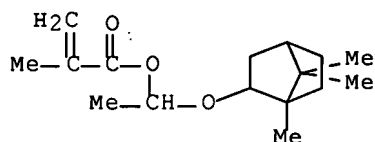
(excimer laser-sensitive photoresists of hemiacetal unsatd. carboxylate polymers for semiconductor devices)

RN 862474-74-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 5-oxo-4-oxatricyclo[4.3.1.1^{3,8}]undec-1-yl 2-methyl-2-propenoate and 1-[(1,7,7-trimethylbicyclo[2.2.1]hept-2-yl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CRN 862474-66-6

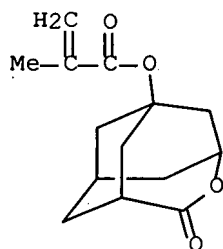
CMF C16 H26 O3



CM 2

CRN 348596-87-2

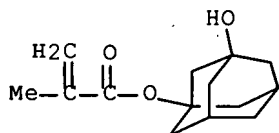
CMF C14 H18 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



IC ICM C07C069-54

ICS C08F020-26; G03F007-039

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 76

IT 474745-04-5P 862474-65-5P 862474-66-6P

(excimer laser-sensitive photoresists of hemiacetal unsatd. carboxylate polymers for semiconductor devices)

IT 862474-73-5P 862474-74-6P

(excimer laser-sensitive photoresists of hemiacetal unsatd.

carboxylate polymers for semiconductor devices)

L9 ANSWER 7 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2005:57488 HCAPLUS Full-text
 DOCUMENT NUMBER: 142:144314
 TITLE: Curable polymer compositions, protective films for
 liquid-crystal displays, and their manufacture
 INVENTOR(S): Baba, Atsushi; Nishikawa, Michinori
 PATENT ASSIGNEE(S): JSR Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 37 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005017321	A	20050120	JP 2003-177752	20030623
			<--	
KR 2005000331	A	20050103	KR 2004-46480	20040622
			<--	

PRIORITY APPLN. INFO.: JP 2003-177752 A 20030623
 <--

ED Entered STN: 21 Jan 2005

AB The compns. comprise (A) polymers having ≥ 2 epoxy groups, (B) cationically polymerizable compds. other than A, and (C) ≥ 1 compds. selected from thiazoles, thiazolines, sulfenamides, dithiocarbamates, and thiurams. The protective films are manufactured by forming films of the compns. on substrates and then irradiating with radiation and/or heating. The protective films are useful for optical devices such as liquid-crystal displays and charge-coupled devices. The compns. show good transparency, heat and load resistance, surface hardness, adhesion strength, and good leveling property for unevenness of color filters.

IT 824955-64-8P, 1-(Cyclohexyloxy)ethyl methacrylate-dicyclopentanyl methacrylate-Epikote 157S65-glycidyl methacrylate-styrene copolymer 824955-65-9P, 1-Cyclohexyloxyethyl methacrylate-dicyclopentanyl methacrylate-glycidyl methacrylate-styrene-trimethylolpropane tris[(3-ethyl-3-oxetanyl)methyl] ether copolymer
 (curable epoxy resin compns. with good load resistance for manufacture of protective films for LCD)

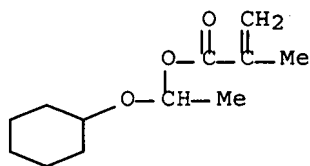
RN 824955-64-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with Epikote 157S65, ethenylbenzene, octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

CMF C12 H20 O3



CM 2

CRN 137598-82-4

CMF Unspecified

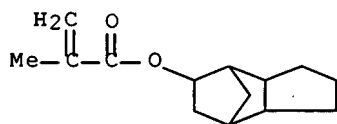
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 34759-34-7

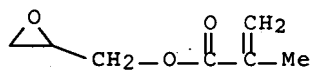
CMF C14 H20 O2



CM 4

CRN 106-91-2

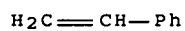
CMF C7 H10 O3



CM 5

CRN 100-42-5

CMF C8 H8



BERNSHTEYN 10/537,120

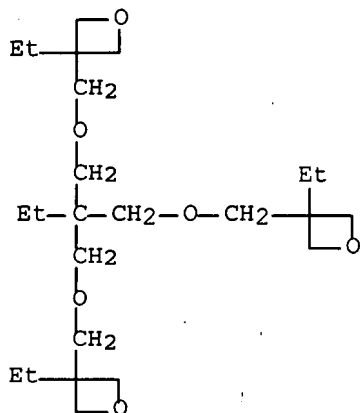
RN 824955-65-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, 3,3'-[[2-ethyl-2-[[[3-ethyl-3-oxetanyl)methoxy)methyl]-1,3-propanediyl]bis(oxyethylene)]bis[3-ethyloxetane], octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 180423-87-4

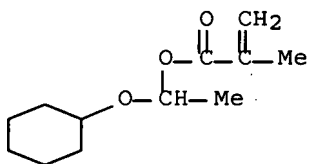
CMF C24 H44 O6



CM 2

CRN 143556-62-1

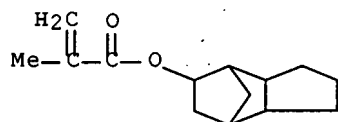
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CM 3.

CRN 34759-34-7

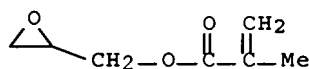
CMF C14 H20 O2



CM 4

CRN 106-91-2

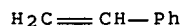
CMF C7 H10 O3



CM 5

CRN 100-42-5

CMF C8 H8



- IC ICM G03F007-038
ICS C08G059-20; C08K005-36; C08L063-00; G02B005-20; G03F007-004
- CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- IT 600737-88-0P, Dicyclopentanyl methacrylate-Epikote 157S65-glycidyl methacrylate-methacrylic acid-styrene copolymer 600737-89-1P, Dicyclopentanyl methacrylate-glycidyl methacrylate-methacrylic acid-styrene-trimethylolpropane tris[(3-ethyl-3-oxetanyl)methyl] ether copolymer 600737-90-4P, N-Cyclohexylmaleimide-Epikote 157S65-glycidyl methacrylate-methacrylic acid-styrene copolymer 756479-35-3P, N-Cyclohexylmaleimide-glycidyl methacrylate-methacrylic acid-styrene-trimethylolpropane tris[(3-ethyl-3-oxetanyl)methyl] ether copolymer 824955-59-1P, 2,4-Diphenyl-4-methyl-1-pentene-Epikote 157S65-glycidyl methacrylate-pyromellitic anhydride-styrene copolymer 824955-60-4P, 2,4-Diphenyl-4-methyl-1-pentene-Epikote 828-glycidyl methacrylate-pyromellitic anhydride-styrene copolymer 824955-61-5P, Dicyclopentanyl methacrylate-2,4-diphenyl-4-methyl-1-pentene-Epikote 157S65-glycidyl methacrylate-pyromellitic anhydride copolymer 824955-63-7P 824955-64-8P, 1-(Cyclohexyloxy)ethyl methacrylate-dicyclopentanyl methacrylate-Epikote 157S65-glycidyl methacrylate-styrene copolymer 824955-65-9P, 1-Cyclohexyloxyethyl methacrylate-dicyclopentanyl methacrylate-glycidyl methacrylate-styrene-trimethylolpropane tris[(3-ethyl-3-oxetanyl)methyl] ether copolymer 824955-66-0P, N-Cyclohexylmaleimide-Epikote 157S65-glycidyl methacrylate-styrene-tetrahydro-2H-pyran-2-yl

BERNSHTEYN 10/537,120 .

methacrylate copolymer 824955-67-1P, N-Cyclohexylmaleimide-glycidyl
methacrylate-styrene-tetrahydropyranyl methacrylate-trimethylolpropane
tris[(3-ethyl-3-oxetanyl)methyl] ether copolymer
(curable epoxy resin compns. with good load resistance for manufacture
of protective films for LCD)

L9 ANSWER 8 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:33665 HCAPLUS Full-text

DOCUMENT NUMBER: 142:103483

TITLE: Storage-stable curable polymer compositions for
protective and planarization films of color
filters

INVENTOR(S): Baba, Atsushi; Nishikawa, Michinori

PATENT ASSIGNEE(S): JSR Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND.	DATE	APPLICATION NO.	DATE
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JP 2005008847	A	20050113	JP 2003-305945	20030829
			<--	
JP 3960281	B2	20070815		
KR 2004103328	A	20041208	KR 2004-37645	20040527
			<--	
PRIORITY APPLN. INFO.:			JP 2003-150242	A 20030528
			<--	
			JP 2003-305945	A 20030829
			<--	

ED Entered STN: 14 Jan 2005

AB The compns., useful for liquid crystal displays, charge-coupled devices, etc.,
comprise (A) cyclocyclic polymers containing epoxy groups chosen from
dicyclopentadiene monoepoxide, epoxycyclohexane, and epoxycyclopentane, and
(B) other cationically polymerizable compds. The protective films show good
storage stability and heat resistance, and improved adhesion.

IT 819070-66-1P

(storage-stable curable polymer compns. for protective and
planarization films of color filters)

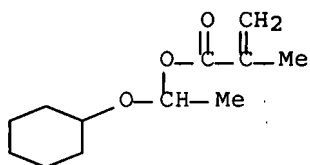
RN 819070-66-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer
with ethenylbenzene, octahydro-4,7-methano-1H-inden-5-yl
2-methyl-2-propenoate and 7-oxabicyclo[4.1.0]hept-3-ylmethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

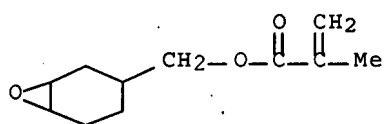
CMF C12 H20 O3



CM 2

CRN 82428-30-6

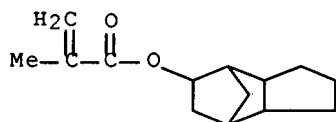
CMF C11 H16 O3



CM 3

CRN 34759-34-7

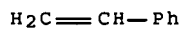
CMF C14 H20 O2



CM 4

CRN 100-42-5

CMF C8 H8



IT 819070-74-1P 819070-76-3P

(storage-stable curable polymer compns. for protective and planarization films of color filters)

RN 819070-74-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with Epikote 157S65, ethenylbenzene, octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and 7-oxabicyclo[4.1.0]hept-3-ylmethyl

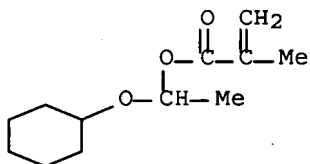
BERNSHTEYN 10/537,120

2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

CMF C12 H20 O3



CM 2

CRN 137598-82-4

CMF Unspecified

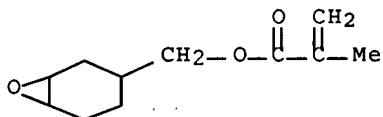
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 82428-30-6

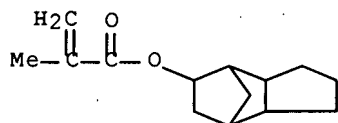
CMF C11 H16 O3



CM 4

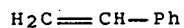
CRN 34759-34-7

CMF C14 H20 O2



CM 5

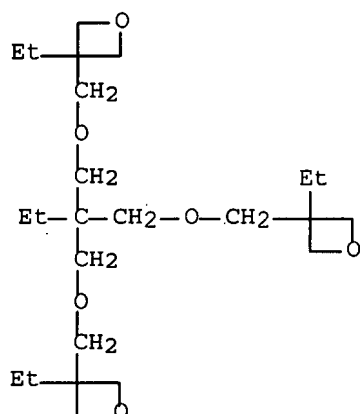
CRN 100-42-5
CMF C8 H8



RN 819070-76-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, 3,3'-[[2-ethyl-2-[[[(3-ethyl-3-oxetanyl)methoxy)methyl]-1,3-propanediyl]bis(oxymethylene)]bis[3-ethyloxetane], octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and 7-oxabicyclo[4.1.0]hept-3-ylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

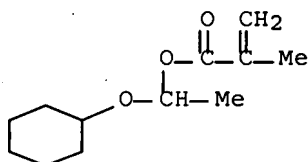
CM 1

CRN 180423-87-4
CMF C24 H44 O6



CM 2

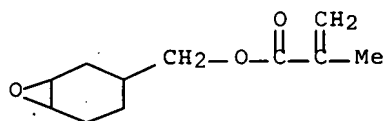
CRN 143556-62-1
CMF C12 H20 O3



CM 3

CRN 82428-30-6

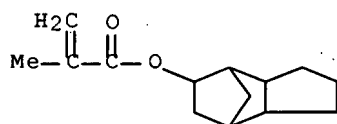
CMF C11 H16 O3



CM 4

CRN 34759-34-7

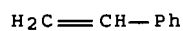
CMF C14 H20 O2



CM 5

CRN 100-42-5

CMF C8 H8



- IC ICM C08F020-32
ICS C08F012-22; C08F016-26; C08F220-02; C08F222-02; C08G059-20
- CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 73
- IT 154065-85-7P, (3,4-Epoxy-cyclohexyl)methyl methacrylate-styrene copolymer 819070-62-7P 819070-64-9P 819070-65-0P
819070-66-1P 819070-67-2P
(storage-stable curable polymer compns. for protective and planarization films of color filters)
- IT 819070-68-3P 819070-69-4P 819070-70-7P 819070-71-8P
819070-72-9P 819070-73-0P 819070-74-1P 819070-75-2P
819070-76-3P 819070-77-4P
(storage-stable curable polymer compns. for protective and planarization films of color filters)

BERNSHTEYN 10/537,120

ACCESSION NUMBER: 2004:779249 HCAPLUS Full-text
DOCUMENT NUMBER: 141:285811
TITLE: Light-sensitive polymerizable resin composition
for fabricating interlayer electrically insulative
films and micro lens and method for manufacturing
product using the same
INVENTOR(S): Takamoto, Eiji; Sano, Kimiyasu; Nishikawa,
Michinori
PATENT ASSIGNEE(S): JSR Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264623	A	20040924	JP 2003-55176	20030303
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TW 266889	B	20061121	TW 2004-93104802	20040225
			<--	
KR 2004078554	A	20040910	KR 2004-13372	20040227
			<--	
PRIORITY APPLN. INFO.:			JP 2003-55176	A 20030303
			<--	

ED Entered STN: 24 Sep 2004

AB The title composition contains a polymer and a photoacid generator, wherein the polymer has epoxy groups and acetal or ketal groups and $\geq 2,000$ weight average mol. weight calculated as polystyrene mol. weight by GPC anal. and wherein the photo-acid generator generates an acid of ≤ 4.0 pKa. The composition shows high sensitivity and good storageability and provides wide development margin and films of good contact with substrate.

IT 760192-27-6P, 1-Cyclohexyloxyethyl methacrylate-styrene-glycidyl methacrylate-2-hydroxyethyl methacrylate- α -Methylstyrene copolymer 760192-30-1P, Tricyclo[5.2.1.0^{2,6}]decanyl methacrylate-1-Cyclohexyloxyethyl methacrylate-styrene-glycidyl methacrylate- α -Methylstyrene copolymer 760192-31-2P, 4-Vinylbenzyl glycidyl ether-1-Cyclohexyloxyethyl methacrylate-styrene-2-hydroxyethyl methacrylate-glycidyl methacrylate- α -Methylstyrene copolymer (light-sensitive polymerizable resin composition)

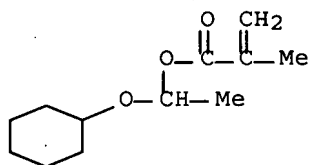
RN 760192-27-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, 2-hydroxyethyl 2-methyl-2-propenoate, (1-methylethenyl)benzene and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

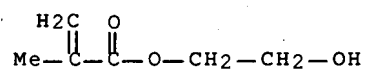
CMF C12 H20 O3



CM 2

CRN 868-77-9

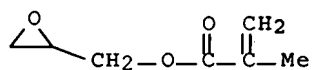
CMF C6 H10 O3



CM 3

CRN 106-91-2

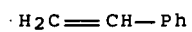
CMF C7 H10 O3



CM 4

CRN 100-42-5

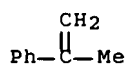
CMF C8 H8



CM 5

CRN 98-83-9

CMF C9 H10



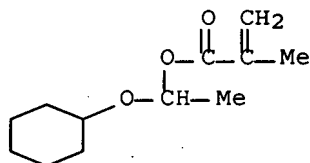
RN 760192-30-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer
with ethenylbenzene, (1-methylethenyl)benzene, octahydro-4,7-methano-
1H-inden-5-yl 2-methyl-2-propenoate and oxiranylmethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

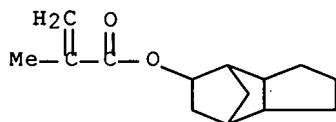
CMF C12 H20 O3



CM 2

CRN 34759-34-7

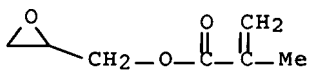
CMF C14 H20 O2



CM 3

CRN 106-91-2

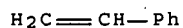
CMF C7 H10 O3



CM 4

CRN 100-42-5

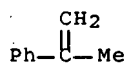
CMF C8 H8



CM 5

CRN 98-83-9

CMF C9 H10



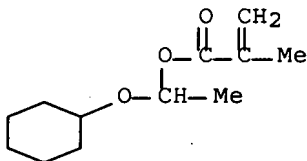
RN 760192-31-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with ethenylbenzene, [[(4-ethenylphenyl)methoxy]methyl]oxirane, 2-hydroxyethyl 2-methyl-2-propenoate, (1-methylethenyl)benzene and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

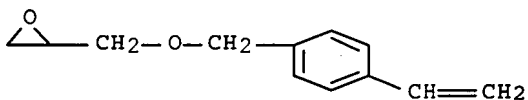
CMF C12 H20 O3



CM 2

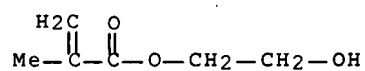
CRN 113538-80-0

CMF C12 H14 O2



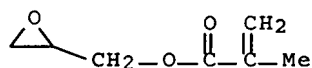
CM 3

CRN 868-77-9
CMF C6 H10 O3



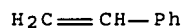
CM 4

CRN 106-91-2
CMF C7 H10 O3



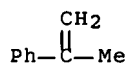
CM 5

CRN 100-42-5
CMF C8 H8



CM 6

CRN 98-83-9
CMF C9 H10



- IC ICM G03F007-038
ICS G02B001-04; G03F007-004
- CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 37, 76
- IT 760192-27-6P, 1-Cyclohexyloxyethyl methacrylate-styrene-glycidyl methacrylate-2-hydroxyethyl methacrylate- α -Methylstyrene copolymer 760192-28-7P, 1-Ethoxyethyl methacrylate-styrene-glycidyl methacrylate-2-hydroxyethyl

BERNSHTEYN 10/537,120.

methacrylate- α -Methylstyrene copolymer 760192-29-8P,
Tetrahydropyranyl methacrylate-styrene-glycidyl methacrylate-2-
hydroxyethyl methacrylate- α -Methylstyrene copolymer
760192-30-1P, Tricyclo[5.2.1.0^{2,6}]decanyl methacrylate-1-
Cyclohexyloxyethyl methacrylate-styrene-glycidyl methacrylate- α -
Methylstyrene copolymer 760192-31-2P, 4-Vinylbenzyl glycidyl
ether-1-Cyclohexyloxyethyl methacrylate-styrene-2-hydroxyethyl
methacrylate-glycidyl methacrylate- α -Methylstyrene copolymer
(light-sensitive polymerizable resin composition)

L9 ANSWER 10 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2004:492719 HCAPLUS Full-text

DOCUMENT NUMBER: 141:62033

TITLE: Cellulose acylate films for optical uses, their
manufacture, and liquid crystal displays and
photographic films employing the same

INVENTOR(S): Kato, Eiichi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004168905	A	20040617	JP 2002-336954	20021120

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PRIORITY APPLN. INFO.: JP 2002-336954 20021120

<--

ED Entered STN: 18 Jun 2004

AB Cellulose acylate dopes containing photopolymn. macromol. initiators
TL1D1(OE1OCOE2CO)nR1 or TL2D2(OCE1CO2E2O)nR2 [T = dithiocarbamate, xanthato;
L1, L2 = bivalent bridging group; E1, E2 = bivalent aliphatic and/or aromatic
group; D1 = CH₂, CO; D2 = O, NH; R1 = OH, OR₅, NR₆R₇ (R₅ = C1-12 hydrocarbyl;
R₆, R₇ = H, C1-12 hydrocarbyl); R₂ = H, C1-12 hydrocarbyl, COR₈, CONHR₉ (R₈,
R₉ = C1-12 hydrocarbyl)], and radical monomers are cast and exposed to light
to form the claimed films. The dopes may contain light-stable monomers and
multifunctional monomers. LCD employing the films are also claimed. Photog.
films having supports comprising 30-250- μ m-thick films obtained as above, are
further claimed. The films show improved flexural strength, storage
stability, transparency, and tear strength.

IT 708212-33-3P

(tear-resistant cellulose acylate films containing radically-polymerized
block copolymers for optical uses)

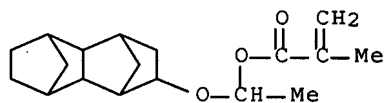
RN 708212-33-3 HCAPLUS

CN Heptanedioic acid, polymer with 1-[(decahydro-1,4:5,8-
dimethanonaphthalen-2-yl)oxy]ethyl 2-methyl-2-propenoate,
decahydro-1,5-naphthalenediol and hexylbutanedioic acid, diblock (9CI)
(CA INDEX NAME)

CM 1

CRN 658060-19-6

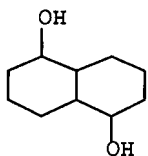
CMF C18 H26 O3



CM 2

CRN 66818-21-1

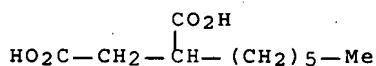
CMF C10 H18 O2



CM 3

CRN 5702-91-0

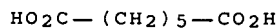
CMF C10 H18 O4



CM 4

CRN 111-16-0

CMF C7 H12 O4



- IC ICM C08F002-44
ICS C08F002-50; C08F251-02; C08J005-18; G02B005-30; G03C001-795;
C08L001-12
- CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)
Section cross-reference(s): 38, 73
- IT 79-41-4DP, Methacrylic acid, diblock polymers 80-62-6DP, Methyl
methacrylate, diblock polymers 105-08-8DP, 1,4-
Cyclohexanedimethanol, diblock polymers 108-30-5DP, Succinic
anhydride, diblock polymers 3066-71-5DP, diblock polymers

BERNSHTEYN 10/537,120

3971-31-1DP, 1,3-Cyclohexanedicarboxylic acid, diblock polymers
 676353-20-1DP, diblock polymers 708212-12-8P 708212-14-0P
 708212-15-1P 708212-16-2P 708212-17-3P 708212-18-4P
 708212-19-5P 708212-20-8P 708212-21-9P 708212-22-0P
 708212-23-1P 708212-24-2P 708212-25-3P 708212-26-4P
 708212-28-6P 708212-29-7P 708212-30-0P 708212-31-1P
 708212-32-2P 708212-33-3P 708212-34-4P 708212-35-5P
 708212-38-8P 708212-40-2P 708212-43-5P 708212-45-7P
 708274-97-9P, 1,6-Hexanediol-glutaric anhydride-methyl methacrylate
 diblock copolymer 708275-31-4P 708275-33-6P 708275-34-7P
 708275-35-8P

(tear-resistant cellulose acylate films containing radically-polymerized
 block copolymers for optical uses)

L9 ANSWER 11 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2004:432933 HCAPLUS Full-text

DOCUMENT NUMBER: 140:431323

TITLE: Cellulose acylate films, their manufacture, and
 optical sheets, polarizers, liquid crystal
 displays, and silver halide photographic materials
 using them

INVENTOR(S): Kato, Eiichi; Moto, Takahiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004148811	A	20040527	JP 2003-349004	20031008

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PRIORITY APPLN. INFO.: JP 2002-294914 A 20021008

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ED Entered STN: 28 May 2004

AB The films, showing good tear strength, moisture impermeability, and storage
 stability and low dependence of retardation on temperature and moisture, are
 manufactured by casting compns. containing cellulose acylates, radically
 polymerizable monomers bearing cycloaliph. hydrocarbon groups, and
 photopolymn. initiators and irradiating them with lights.

IT 658060-20-9P

(manufacture of cellulose acylate films with good storage stability and
 low dependence of retardation on temperature and moisture for optical
 films, polarizers, and photog. films)

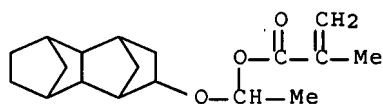
RN 658060-20-9 HCAPLUS

CN Butanedioic acid, 5-[4-(5-chloro-2H-benzotriazol-2-yl)-5-hydroxy-2-
 methylphenoxy]-2-hydroxypentyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl
 ester, polymer with 1-[(decahydro-1,4:5,8-dimethanonaphthalen-2-
 yl)oxy]ethyl 2-methyl-2-propenoate and 3-[(1-ethyl-2,2,6,6-tetramethyl-
 4-piperidinyloxy)-2-hydroxypropyl 2-methyl-2-propenoate (9CI) (CA
 INDEX NAME)

CM 1

CRN 658060-19-6

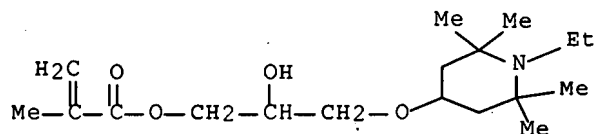
CMF C18 H26 O3



CM 2

CRN 658059-88-2

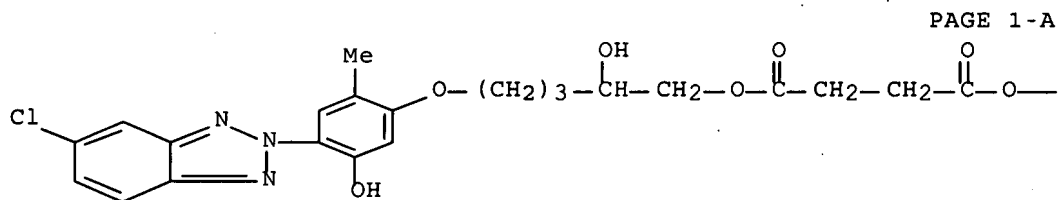
CMF C18 H33 N O4



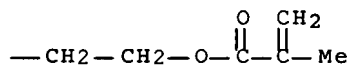
CM 3

CRN 658059-87-1

CMF C28 H32 Cl N3 O9



PAGE 1-A



PAGE 1-B

IC ICM B29C041-24

ICS G02B005-30; G02F001-1335; G03C001-795; B29K001-00; B29L007-00

CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT	99732-63-5P	658059-80-4P	658059-82-6P	658060-11-8P
	658060-13-0P	658060-20-9P	658063-12-8P	658063-14-0P
	676265-38-6P	676265-41-1P	693274-42-9P	693274-43-0P
	693274-44-1P	693274-45-2P	693274-46-3P	693274-47-4P

BERNSHTEYN 10/537,120

693274-49-6P 693274-50-9P 693274-51-0P 693274-52-1P
693287-19-3P 693287-22-8P 693287-25-1P

(manufacture of cellulose acylate films with good storage stability and low dependence of retardation on temperature and moisture for optical films, polarizers, and photog. films)

L9 ANSWER 12 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2004:351517 HCAPLUS Full-text

DOCUMENT NUMBER: 140:383173

TITLE: Cellulose acylate films, their manufacture, and optical films, liquid crystal displays, and photographic materials employing the same

INVENTOR(S): Kato, Eiichi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 52 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004130674	A	20040430	JP 2002-297744	20021010

PRIORITY APPLN. INFO.: JP 2002-297744 20021010

ED Entered STN: 30 Apr 2004

AB Cellulose acylate dopes containing macromol. photopolymn. initiators TL[CHA1CA2(V1R)] [T = SC:SNR11R12, SC:SOR13 (R11, R12 = H, hydrocarbyl; R13 = hydrocarbyl); L = bivalent bridging group; A1, A2 = H, halo, cyano, alkyl, CH2CO2Q2 (Q2 = alkyl); V1 = CO2, OCO, CH2OCO, etc.; R = aliphatic or aromatic group] and radical monomers are cast on supports and exposed to light to form films with high tear strength and excellent transparency for the title mentioned uses. Monomers having light-stabilized groups may be incorporated in the said monomers. The films for photog. film supports have thickness 30-250 µm.

IT 684282-38-0P

(manufacture of cellulose acylate films having excellent tear strength and transparency for optical, photog., and display uses)

RN 684282-38-0 HCAPLUS

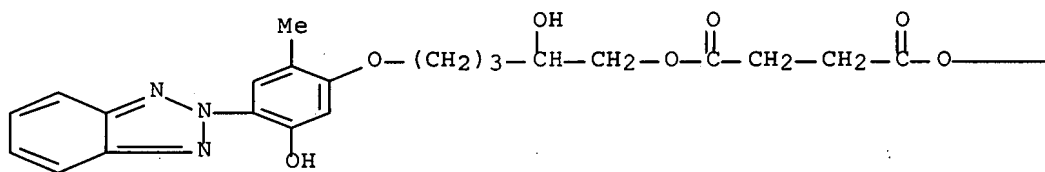
CN Butanedioic acid, 5-[4-(2H-benzotriazol-2-yl)-5-hydroxy-2-methylphenoxy]-2-hydroxypentyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with cyclohexyl 2-propenoate, 1-[(decahydro-1,4:5,8-dimethanonaphthalen-2-yl)oxy]ethyl 2-methyl-2-propenoate, 3-[(1-ethyl-2,2,6,6-tetramethyl-4-piperidinyl)oxy]-2-hydroxypropyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and 3,3,4,4,5,5,6,6,6-nonafluorohexyl 2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

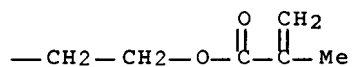
CRN 684282-22-2

CMF C28 H33 N3 O9

PAGE 1-A



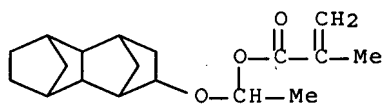
PAGE 1-B



CM 2

CRN 658060-19-6

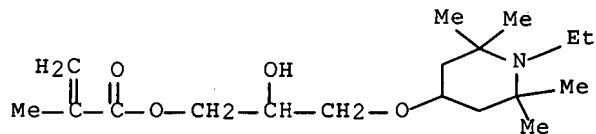
CMF C18 H26 O3



CM 3

CRN 658059-88-2

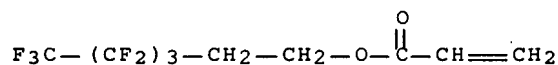
CMF C18 H33 N O4



CM 4

CRN 52591-27-2

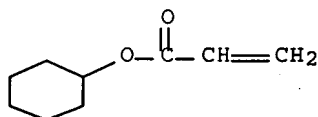
CMF C9 H7 F9 O2



CM 5

CRN 3066-71-5

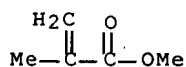
CMF C9 H14 O2



CM 6

CRN 80-62-6

CMF C5 H8 O2



- IC . ICM B29C041-28
ICS B29C041-50; C08F002-44; C08F002-50; C08F251-02; C08J005-18;
G02B005-30; G03C001-795; B29K001-00; B29L007-00; C08L001-12
- CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)
Section cross-reference(s): 38, 73
- IT 80-62-6DP, Methyl methacrylate, block polymers with light-stabilized
monomers and macromol. initiators 96-33-3DP, Methyl acrylate, block
polymers with light-stabilized monomers 101-43-9DP, Cyclohexyl
methacrylate, block polymers with light-stabilized monomers
142-09-6DP, Hexyl methacrylate, block polymers with light-stabilized
monomers and macromol. initiators 110506-07-5DP,
4-Trifluoromethylphenyl methacrylate, block polymers with
light-stabilized monomers and macromol. initiators 111404-23-0DP,
block polymers with light-stabilized monomers 121601-93-2DP,
1-Adamantyl acrylate, block polymers with light-stabilized monomers
and macromol. initiators 134291-01-3P, Cyclohexyl
methacrylate-methyl methacrylate block copolymer 684282-17-5P
684282-18-6P 684282-19-7P 684282-20-0P 684282-21-1P, Cyclohexyl
methacrylate-vinyl acetate-styrene block copolymer 684282-23-3P
684282-24-4P 684282-25-5P 684282-26-6P 684282-27-7P
684282-28-8P 684282-29-9P 684282-30-2P 684282-31-3P
684282-32-4P 684282-33-5P 684282-34-6P 684282-35-7P
684282-36-8P 684282-37-9P 684282-38-0P 684282-39-1P
(manufacture of cellulose acrylate films having excellent tear strength)

BERNSHTEYN 10/537,120

and transparency for optical, photog., and display uses)

L9 ANSWER 13 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2004:271645 HCAPLUS Full-text

DOCUMENT NUMBER: 140:294934

TITLE: Cellulose acylate composite films, their manufacture, and their uses in optical films, liquid crystal displays, and photographic materials

INVENTOR(S): Kato, Eiichi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004099775	A	20040402	JP 2002-264588	20020910

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PRIORITY APPLN. INFO.: JP 2002-264588 20020910

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ED Entered STN: 02 Apr 2004

AB The films are manufactured by casting cellulose acylate compns. containing radically-polymerizable monomers, cationically-polymerizable monomers, and photopolymn. initiators and irradiating the compns. with electron beam (sic). Also claimed are optical films and liquid crystal displays using the films and Ag halide photog. materials using the films with thickness 30-250 μ m as supports. The films show low haze, high tear strength, good weatherability, and neither contamination with foreign substances nor stains. A polarizer film prepared by laminating both sides of an iodine-adsorbed PVA-based polarizer with a pair of the composite cellulose triacetate films shows high durability.

IT 658060-20-9P

(manufacture of cellulose acylate films for LCD, photog. materials, etc., from dopes containing radically-polymerizable monomers, cationically-polymerizable monomers, and photoinitiators)

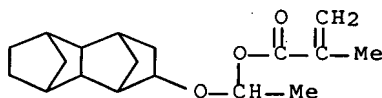
RN 658060-20-9 HCAPLUS

CN Butanedioic acid, 5-[4-(5-chloro-2H-benzotriazol-2-yl)-5-hydroxy-2-methylphenoxy]-2-hydroxypentyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with 1-[(decahydro-1,4:5,8-dimethanonaphthalen-2-yl)oxy]ethyl 2-methyl-2-propenoate and 3-[(1-ethyl-2,2,6,6-tetramethyl-4-piperidinyl)oxy]-2-hydroxypropyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 658060-19-6

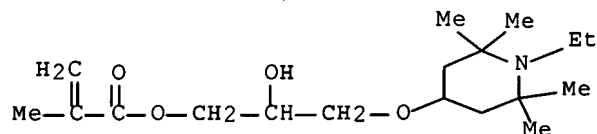
CMF C18 H26 O3



CM 2

CRN 658059-88-2

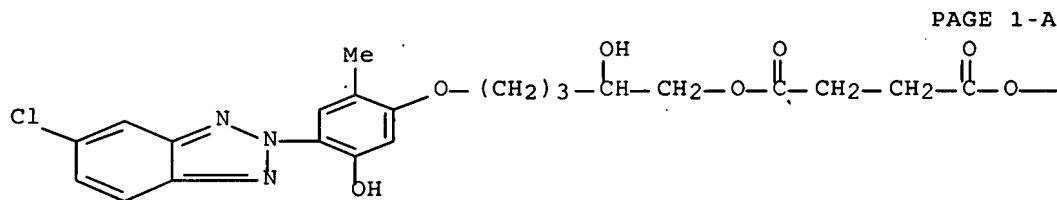
CMF C18 H33 N O4



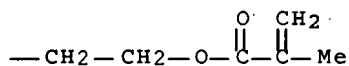
CM 3

CRN 658059-87-1

CMF C28 H32 Cl N3 O9



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PAGE 1-B

IC ICM C08G085-00

ICS B29C041-24; C08J005-18; C08L001-10; C08L101-00; G03C001-795;
B29K001-00; B29L007-00CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)

Section cross-reference(s): 38, 43, 73

IT 9011-14-7P, Methyl methacrylate homopolymer 25085-98-7P
 26283-70-5P, Hydrogenated bisphenol A diglycidyl ether homopolymer
 99732-63-5P 658059-80-4P 658059-82-6P 658059-84-8P
 658059-86-0P 658060-14-1P 658060-20-9P 658060-24-3P
 658060-26-5P 658063-14-0P 676265-21-7P 676265-23-9P
 676265-25-1P 676265-27-3P 676265-28-4P 676265-29-5P
 676265-31-9P 676265-33-1P 676265-34-2P 676265-38-6P
 676265-41-1P 676265-43-3P 676265-45-5P 676265-48-8P
 676265-49-9P 676265-51-3P 676266-16-3P 676266-18-5P

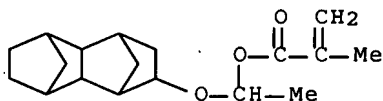
BERNSHTEYN 10/537,120.

(manufacture of cellulose acylate films for LCD, photog. materials, etc., from dopes containing radically-polymerizable monomers, cationically-polymerizable monomers, and photoinitiators)

L9 ANSWER 14 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2004:180035 HCAPLUS Full-text
 DOCUMENT NUMBER: 140:243664
 TITLE: Cellulose acylate films with excellent transparency, tear strength, and weather resistance, their manufacture, and optical films, liquid crystal displays, and silver halide photographic materials using them
 INVENTOR(S): Kato, Eiichi
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 52 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004067816	A	20040304	JP 2002-227579	20020805
			<--	
PRIORITY APPLN. INFO.:			JP 2002-227579	20020805
			<--	

ED Entered STN: 05 Mar 2004
 AB The films are manufactured by casting cellulose acylate compns. containing polymerizable monomers, photothermal converting agents, and thermal polymerization initiators and irradiating them with IR.
 IT 666837-50-9P
 (manufacture of cellulose acylate cast films with good transparency, tear strength, and weather resistance for optical use)
 RN 666837-50-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-[(decahydro-1,4:5,8-dimethanonaphthalen-2-yl)oxy]ethyl ester, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 658060-19-6
 CMF C18 H26 O3



IC ICM C08J005-18
 ICS B29C041-28; B29C041-50; C08F002-44; C08F251-02; G02B005-30;
 G02F001-1335; G03C001-795; B29K001-00; B29L007-00; C08L001-10
 CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38, 73
 IT 2495-35-4DP, polymers 9011-14-7P, Methyl methacrylate polymer
 16868-15-8DP, polymers 40756-50-1P 59620-20-1DP, polymers

BERNSHTEYN 10/537,120 .

72355-89-6P 99732-63-5P 119347-00-1DP, polymers 128611-70-1DP,
 polymers 151543-64-5P, Poly(1,4-cyclohexanedimethanol divinyl ether)
 658059-80-4P 658059-82-6P 658059-84-8P 658059-86-0P
 658059-89-3P 658059-91-7P 658059-97-3P 658060-00-5P
 658060-03-8P 658060-06-1P 658060-09-4P 658060-36-7P
 658060-38-9DP, polymers 666837-41-8P 666837-45-2P 666837-46-3P
 666837-47-4P 666837-48-5P 666837-49-6P 666837-50-9P
 666837-51-0P 666837-52-1P 666837-53-2P 666837-56-5DP, reaction
 products with monoepoxide 666837-57-6DP, reaction products with
 epoxy resin 666841-65-2P 666841-66-3P
 (manufacture of cellulose acylate cast films with good transparency,
 tear strength, and weather resistance for optical use)

L9 ANSWER 15 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2004:117562 HCAPLUS Full-text
 DOCUMENT NUMBER: 140:189907
 TITLE: Cellulose acylate films, their manufacture,
 optical films, liquid-crystal displays, and silver
 halide photographic materials
 INVENTOR(S): Kato, Eiichi
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 61 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004042381	A	20040212	JP 2002-201749	20020710

PRIORITY APPLN. INFO.: JP 2002-201749 20020710
 <--

OTHER SOURCE(S): MARPAT 140:189907

ED Entered STN: 13 Feb 2004

AB The films are manufactured by (1) applying cellulose acylate compns.
 containing polymerizable monomers, photopolymn. initiators, and spectral
 sensitizers Ar1R3C:CR2C(:X)R1 [R1-R3 = H, monovalent nonmetal atomic group;
 R1-R3 may form acidic nucleus of dyes; Ar1 = aryl group having OR4, NR5,
 and/or SR6 at o- or p-position; X = O, S, :NR7; R4-R7 = (un)substituted alkyl
 or aryl] and (2) irradiating with UV light. The photog. materials have
 supports of the films with thickness 30-250 µm. The films show high bending
 and tear strength and good storage stability.

IT 658060-20-9P

(manufacture of cellulose acylate films with high tear strength for LCD
 and photog. materials)

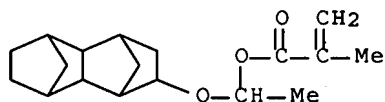
RN 658060-20-9 HCAPLUS

CN Butanedioic acid, 5-[4-(5-chloro-2H-benzotriazol-2-yl)-5-hydroxy-2-
 methylphenoxy]-2-hydroxypentyl 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl
 ester, polymer with 1-[(decahydro-1,4:5,8-dimethanonaphthalen-2-
 yl)oxy]ethyl 2-methyl-2-propenoate and 3-[(1-ethyl-2,2,6,6-tetramethyl-
 4-piperidinyl)oxy]-2-hydroxypropyl 2-methyl-2-propenoate (9CI) (CA
 INDEX NAME)

CM 1

CRN 658060-19-6

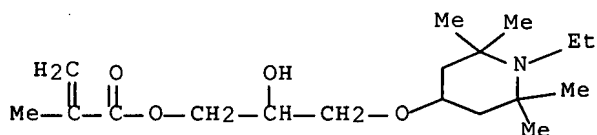
CMF C18 H26 O3



CM 2

CRN 658059-88-2

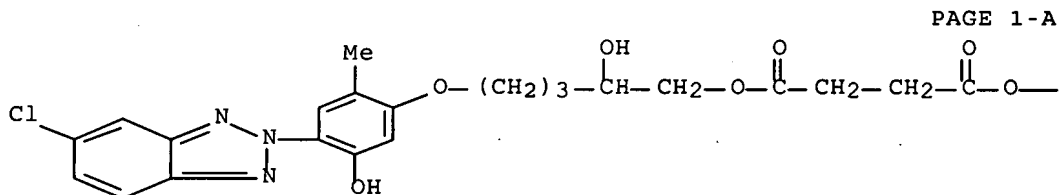
CMF C18 H33 N O4



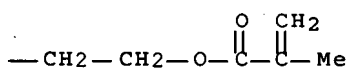
CM 3

CRN 658059-87-1

CMF C28 H32 Cl N3 O9



PAGE 1-A



PAGE 1-B

IC ICM B29C041-24

ICS B29C041-50; C08F002-44; C08F002-50; C08F251-02; C08J005-18;

G02B005-30; G02F001-1335; B29K001-00; B29L007-00; C08L001-10

CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 73

IT 9011-14-7P, Methyl methacrylate homopolymer 99732-63-5P

658059-80-4P 658059-82-6P 658059-84-8P 658059-85-9P

BERNSHTEYN 10/537,120

658059-86-0P 658059-89-3P 658059-91-7P 658059-94-0P
 658059-97-3P 658060-00-5P 658060-03-8P 658060-06-1P
 658060-09-4P 658060-11-8P 658060-13-0P 658060-14-1P
 658060-16-3P 658060-18-5P 658060-20-9P 658060-21-0P
 658060-23-2P 658060-24-3P 658060-26-5P 658060-30-1P
 658060-33-4P 658060-36-7P 658060-40-3P 658060-43-6P
 658063-12-8P 658063-14-0P

(manufacture of cellulose acylate films with high tear strength for LCD and photog. materials)

L9 ANSWER 16 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2003:585195 HCAPLUS Full-text
 DOCUMENT NUMBER: 139:133273
 TITLE: Preparation of (meth)acryloyl-containing
 adamantane derivatives
 INVENTOR(S): Anzai, Ryuichi; Kikuchi, Katsuaki
 PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokyo Koho, 8 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003212823	A	20030730	JP 2002-10155	20020118

PRIORITY APPLN. INFO.: JP 2002-10155 20020118
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OTHER SOURCE(S): MARPAT 139:133273

ED Entered STN: 30 Jul 2003

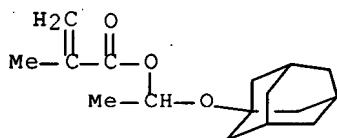
AB CH:CR1CO2CHMeO(CH2)nR2 [I; R1 = H, Me; R2 = (un)substituted adamantyl, adamantanonyl (sic); n = 0-4], useful as materials for drugs, agrochems., polymers, etc., are prepared by treating CH:CR1CO2CH:CH2 (R1 = same as above) with R2(CH2)nOH (R2 = same as above), preferably in the presence of acid catalysts. Alternatively I are prepared by treating CH:CR1CO2H with R2(CH2)nOH:CH2. A mixture of 1-adamantanol, vinyl acrylate, and Bi(OSO2CF3)3.4H2O was heated at 40° for 8 h to give 53% I (R1 = H, R2 = 1-adamantyl, n = 0).

IT 279218-82-5P 569329-57-3P 569329-58-4P
 569329-60-8P 569329-61-9P 569329-62-0P
 569329-64-2P 569329-66-4P

(preparation of (meth)acryloyl-containing adamantane derivs. from vinyl (meth)acrylate and adamantyl alcs. or from (meth)acrylic acid and adamantyl alcs.)

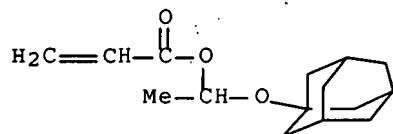
RN 279218-82-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(tricyclo[3.3.1.1.3,7]dec-1-yloxy)ethyl ester (9CI) (CA INDEX NAME)



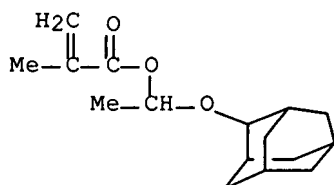
RN 569329-57-3 HCAPLUS

CN 2-Propenoic acid, 1-(tricyclo[3.3.1.1^{3,7}]dec-1-yloxy)ethyl ester (9CI)
(CA INDEX NAME)



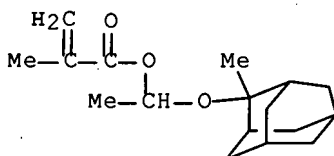
RN 569329-58-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(tricyclo[3.3.1.1^{3,7}]dec-2-yloxy)ethyl ester (9CI) (CA INDEX NAME)



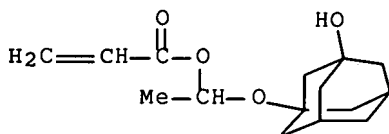
RN 569329-60-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



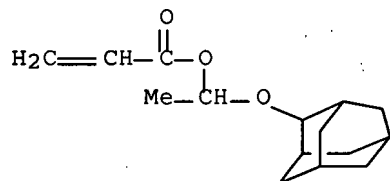
RN 569329-61-9 HCAPLUS

CN 2-Propenoic acid, 1-[(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



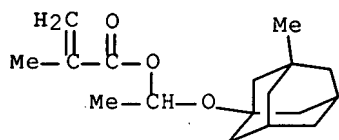
RN 569329-62-0 HCAPLUS

CN 2-Propenoic acid, 1-(tricyclo[3.3.1.1^{3,7}]dec-2-yloxy)ethyl ester (9CI)
(CA INDEX NAME)



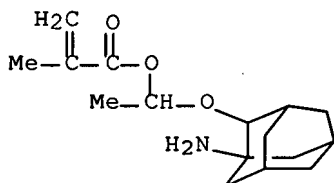
RN 569329-64-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(3-methyltricyclo[3.3.1.1^{3,7}]dec-1-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



RN 569329-66-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(1-aminotricyclo[3.3.1.1^{3,7}]dec-2-yl)oxy]ethyl ester (9CI) (CA INDEX NAME)



IC ICM C07C067-04

ICS C07C067-29; C07C069-54; C07C213-08; C07C217-52; C07B061-00

CC 24-8 (Alicyclic Compounds)

Section cross-reference(s): 35

IT 279218-82-5P 569329-57-3P 569329-58-4P

569329-59-5P 569329-60-8P 569329-61-9P

569329-62-0P 569329-64-2P 569329-66-4P

(preparation of (meth)acryloyl-containing adamantane derivs. from vinyl (meth)acrylate and adamantyl alcs. or from (meth)acrylic acid and adamantyl alcs.)

L9 ANSWER 17 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2003:257923 HCAPLUS Full-text

DOCUMENT NUMBER: 138:273081

TITLE: Carboxyl-blocked polyfumarates, their preparation, their coatings, and their uses as electronic

encapsulants
 INVENTOR(S): Okuo, Masaki; Sonoda, Kensaku; Sato, Hiroshi
 PATENT ASSIGNEE(S): NOF Corporation, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003096137	A	20030403	JP 2001-292850	20010926

PRIORITY APPLN. INFO.: JP 2001-292850 20010926
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ED Entered STN: 03 Apr 2003

AB Fumarate diesters CH:(CO2X1)CHCO2X2 (X1, X2 = C3-8 alkyl, C4-8 cycloalkyl) are radically polymerized with (M1) CH:(CO2A1)CHCO2A2 [A1, A2 = same definition as X1 and X2, where one or both of them are CR1(CHR2R3)Y1R4 (R1-R3 = H, C1-18 organic group; R4 = C1-18 organic group; Y1 = O, S) or Q (R5, R6 = H, C1-18 organic group; R7, R8 = bivalent C1-18 organic group; Y2 = O, S)], (M2) CH2:C(CH2CO2B1)(CO2B2) [B1, B2 = C3-8 alkyl, C4-8 cycloalkyl, where one or both of them are Q (aforesaid)], and/or (M3) CH2:CEDnCO2Z1 [Z1 = Q (aforesaid); D= benzyl; n = 0, 1; E = H, Me] to form the title mentioned polyfumarates satisfying Mn 1000-300,000 and acid value, when the carboxyl groups are unblocked, 50-250 mg-KOH/g. Also claimed are coatings containing (A) the polyfumarates, (B) their latent crosslinking agents, (C) latent acid catalysts, and (D) self-crosslinkable polymers which have M2 (aforesaid)-derived units and substituted ethylene units containing carboxyl-reactive functional groups, preferably in weight ratio of A/B/C/D 100:(5-2000):(0.01-15):(5-500). Cured films of the coatings, satisfying Knoop hardness 8-12, are further claimed. Thus, a clear coating containing 100 parts dicyclohexyl fumarate-di-sec-Bu fumarate-bis(2-isobutyloxyethyl) fumarate copolymer (acid value of unblocked form 51 mg-KOH/g, Mw 35,000) and 15.5 parts Denacol EX 421 (epoxy resin) was applied on a pretreated steel sheet and baked at 140° to give a specimen showing excellent resistance to impact, acid, and accelerated weathering test and Knoop microhardness 10.2.

IT 503269-35-0P

(storage-stable coatings of polyfumarates having latent carboxyl groups suited for electronic encapsulants)

RN 503269-35-0 HCAPLUS

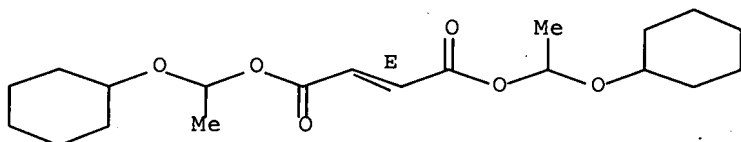
CN 2-Butenedioic acid (2E)-, bis[1-(cyclohexyloxy)ethyl] ester, polymer with bis(1-methylethyl) (2E)-2-butenedioate (9CI) (CA INDEX NAME)

CM 1.

CRN 503269-34-9

CMF C20 H32 O6

Double bond geometry as shown.

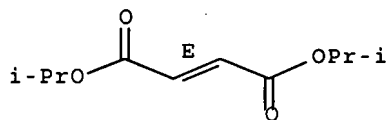


CM 2

CRN 7283-70-7

CMF C10 H16 O4

Double bond geometry as shown.



IC ICM C08F222-14
 ICS C08G085-00; H01L023-29; H01L023-31
 CC 42-10 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 37, 38, 76
 IT 503269-33-8P 503269-35-0P 503269-37-2P 503269-39-4P
 503269-41-8P 503269-43-0P 503269-44-1P
 (storage-stable coatings of polyfumarates having latent carboxyl groups suited for electronic encapsulants)

L9 ANSWER 18 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2003:132379 HCAPLUS Full-text
 DOCUMENT NUMBER: 138:154784
 TITLE: Sheet-forming actinic energy ray-curable resins for optical instruments
 INVENTOR(S): Sauchi, Yasuyuki; Igarashi, Ichiro; Matsuda, Yutaka; Tanaka, Junji
 PATENT ASSIGNEE(S): Toa Gosei Chemical Industry Co., Ltd., Japan; Sumitomo Bakelite Co., Ltd.
 SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003048922	A	20030221	JP 2001-237635	20010806

PRIORITY APPLN. INFO.: JP 2001-237635 20010806
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ED Entered STN: 21 Feb 2003

AB The resins for forming heat-resistant, transparent sheets, contain (A) alkoxyated bis(hydroxyphenyl)fluorene di(meth)acrylates and optionally (B) photopolymerization initiators and (C) thermal polymerization initiators. Thus, a 99:1 bisphenoxyethanol fluorene diacrylate-1-hydroxycyclohexyl Ph ketone mixture was cast on a framed glass plate and exposed to UV to give a 0.4-mm thick sheet showing color difference (JIS K 5400, after 1 h at 210°) ΔE 8.6 and ΔY 12.5, Tg 167°, and water absorption 0.8% after 20 h in 80°-water.

IT 496046-49-2P
 (actinic energy ray-curable resins for heat-resistant transparent optical sheets)

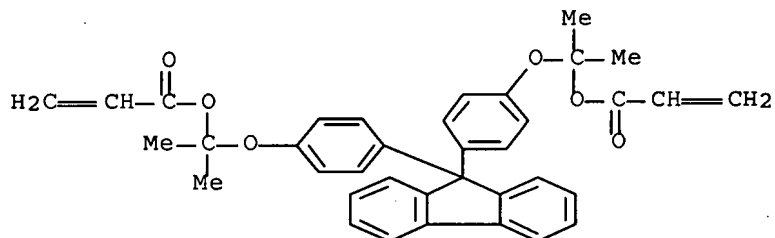
BERNSHTEYN 10/537,120

RN 496046-49-2 HCAPLUS
 CN 2-Propenoic acid, 9H-fluoren-9-ylidenebis[4,1-phenyleneoxy(1-methylethylidene)] ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 496046-48-1

CMF C37 H34 O6



IC ICM C08F020-30
 ICS C08F290-06; G02B001-04
 CC 38-3 (Plastics Fabrication and Uses)
 Section cross-reference(s): 73
 IT 246858-42-4P 496046-49-2P
 (actinic energy ray-curable resins for heat-resistant transparent optical sheets)

L9 ANSWER 19 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2001:444554 HCAPLUS Full-text
 DOCUMENT NUMBER: 135:45937
 TITLE: Preparation of alkoxymethyl ester dendrimers for photoresists
 INVENTOR(S): Sadayori, Naoki; Mochizuki, Makoto; Yoshioka, Masahiro
 PATENT ASSIGNEE(S): Nitto Denko Corp., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 5 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001163971	A	20010619	JP 1999-352920	19991213

PRIORITY APPLN. INFO.: JP 1999-352920 19991213

OTHER SOURCE(S): CASREACT 135:45937; MARPAT 135:45937

ED Entered STN: 20 Jun 2001

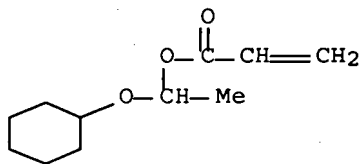
AB The dendrimers [R₂N(CH₂)₃]₂N(CH₂)₄N[(CH₂)₃NR₂]₂ [R = R₂OCHR₁OCOCH₂CH₂; R₁, R₂ = C₁-6 alkyl, C₃-8 alicyclic alkyl; R₁R₂ may form ring] are prepared by reaction of [H₂N(CH₂)₃]₂N(CH₂)₄N[(CH₂)₃NH₂]₂ with R₂OCHR₁OCOCH:CH₂ (R₁, R₂ = same as above) in the presence of catalysts in solvents. [H₂N(CH₂)₃]₂N(CH₂)₄N[(CH₂)₃NH₂]₂ was reacted with 1-ethoxyethyl acrylate at 40° for 18 h to give 93% dendrimer.

IT 153206-78-1

(preparation of alkoxyethyl ester dendrimers by addition acrylates with polypropyleneimine dendrimers)

RN 153206-78-1 HCAPLUS

CN 2-Propenoic acid, 1-(cyclohexyloxy)ethyl ester (9CI) (CA INDEX NAME)



IC ICM C08G073-02

ICS C07C227-10; C07C229-16

CC 23-17 (Aliphatic Compounds)

Section cross-reference(s): 74

IT 52351-91-4, 1-Ethoxyethyl acrylate 52858-57-8, 2-Tetrahydropyranyl
acrylate 120239-63-6 148740-50-5 153206-78-1
344744-36-1

(preparation of alkoxyethyl ester dendrimers by addition acrylates with polypropyleneimine dendrimers)

L9 ANSWER 20 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2000:454439 HCAPLUS Full-text

DOCUMENT NUMBER: 133:96789

TITLE: Positive-working photoresist composition for far UV ray exposure

INVENTOR(S): Sato, Kenichiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 30 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000187327	A	20000704	JP 1998-327056	19981117

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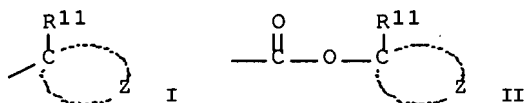
PRIORITY APPLN. INFO.:

JP 1998-293986 A 19981015

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ED Entered STN: 06 Jul 2000

GI



AB The title photoresist composition contains (a) a compound which generates an acid by irradiation with activated ray or radiation and (b) a resin which contains alkali-soluble groups protected with ≥ 1 of acid-cleaving alicyclic hydrocarbon-containing partial structures I, CR12R13R14, CH(OR15)R16, CR19R21CR17:CR18R20, CR22R25CHR23COR24, and II (R11 = Me, Et, Pr, iso-Pr, Bu, iso-Bu, sec-Bu; Z = atoms required to form an alicyclic hydrocarbon group with the C atom; R12-16 = C1-4 alkyl, alicyclic hydrocarbon; ≥ 1 of R12-14, or R15 or R16 are alicyclic hydrocarbons; R17-21 = straight-chain or branched alkyl or alicyclic hydrocarbon, ≥ 1 of R17-21 is an alicyclic hydrocarbon, R19 or R21 is a C1-4 alkyl or alicyclic hydrocarbon; R22-25 = C1-4 alkyl or alicyclic hydrocarbon, ≥ 1 of R22-25 is an alicyclic hydrocarbon), and (c) a low-mol.-weight compound having hydrophilic functional and cyclic hydrocarbon groups or a naphthalene compound having hydrophilic functional groups. The composition shows improved developability and high sensitivity toward far UV rays including excimer laser beams and give ultra-fine patterns.

IT 279218-83-6P

(pos.-working photoresist composition for far UV ray exposure)

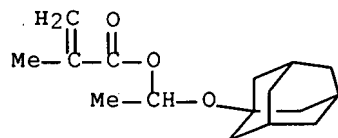
RN 279218-83-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, tetrahydro-4-methyl-2-oxo-2H-pyran-4-yl ester, polymer with 1-(tricyclo[3.3.1.1^{3,7}]dec-1-yloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 279218-82-5

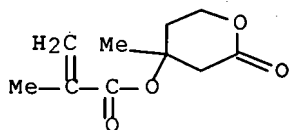
CMF C16 H24 O3



CM 2

CRN 177080-66-9

CMF C10 H14 O4



IC ICM G03F007-039

ICS G03F007-20; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 83-56-7P, 1,5-Dihydroxynaphthalene 86-55-5P, 1-Naphthalenecarboxylic

BERNSHTEYN 10/537,120

acid 90-15-3P, 1-Naphthol 92-70-6P, 3-Hydroxy-2-naphthalenecarboxylic acid 571-60-8P, 1,4-Dihydroxynaphthalene 581-96-4P, 2-Naphthylacetic acid 828-51-3P, 1-Adamantane carboxylic acid 7432-73-7P 177080-68-1P 181531-13-5P, 2-Methyladamantyl methacrylate-3-oxocyclohexyl methacrylate copolymer 244088-20-8P 279218-77-8P 279218-83-6P 280123-19-5P 280123-22-0P

(pos.-working photoresist composition for far UV ray exposure)

L9 ANSWER 21 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2000:440245 HCAPLUS Full-text

DOCUMENT NUMBER: 133:81565

TITLE: Positive-working photoresist composition for far UV ray exposure

INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

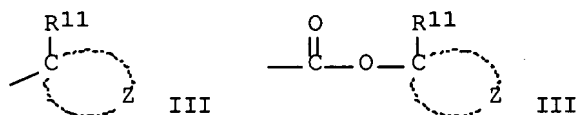
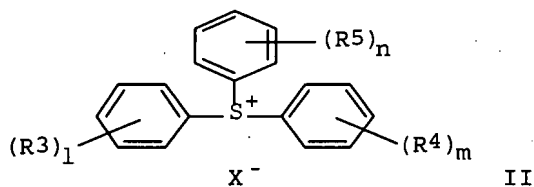
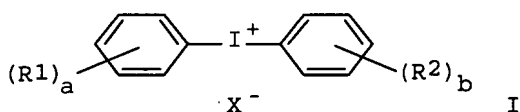
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000181054	A	20000630	JP 1998-327055	19981117
			<--	
JP 3476374	B2	20031210		
PRIORITY APPLN. INFO.:			JP 1998-288108	A 19981009
			<--	

OTHER SOURCE(S): MARPAT 133:81565

ED Entered STN: 30 Jun 2000

GI



AB The title photoresist composition contains (a) a compound I or II [R1-5 = H, alkyl, cycloalkyl, alkoxy, alkoxy carbonyl, acyl, acyloxy (which may be

substituted), NO₂, halo, OH, CO₂H, ≥1 of R₁ and R₂ is a C_{≥5} alkyl, cycloalkyl, alkoxy, alkoxy carbonyl, acyl or acyloxy group (substituted); a, b, l = 1-5; m, n = 0-5, when l + m + n = 1, R₃ is an alkyl, cycloalkyl, alkoxy, alkoxy carbonyl, acyl or acyloxy group (substituted); X = RSO₂ (R = aliphatic or aromatic hydrocarbon which may be substituted)] which generates a sulfonic acid by irradiation with activating ray or radiation and (b) a resin which contains alkali-soluble groups protected with ≥1 of alicyclic hydrocarbon-containing partial structures III, CR₁₂R₁₃R₁₄, CH(OR₁₅)R₁₆, CR₁₉R₂₁CR₁₇:CR₁₈R₂₀, CR₂₂R₂₅CHR₂₃COR₂₄, and IV [(R₁₁ = Me, Et, Pr, iso-Pr, Bu, iso-Bu, sec-Bu; Z = atoms required to form an alicyclic hydrocarbon group along with the C atom); R₁₂-R₁₆ = C₁-4 straight-chain or branched alkyl or alicyclic hydrocarbon, ≥1 of R₁₂-R₁₆ and either R₁₅ or R₁₆ are alicyclic hydrocarbons; R₁₇-R₂₁ = H, C₁-4 straight-chain or branched alkyl or alicyclic hydrocarbon, ≥1 of R₁₇-R₂₁ is an alicyclic is a C₁-4 straight-chain or branched alkyl or alicyclic hydrocarbon; R₂₂-R₂₅ = C₁-4 straight-chain or branched alkyl or alicyclic hydrocarbon, ≥1 of R₂₂-R₂₅ is an alicyclic hydrocarbon] and is cleaved by the action of acid to increase the solubility to alkali. The solution of the composition in organic solvents shows improved storage stability and the composition exhibits high sensitivity toward far UV rays, especially ArF excimer laser beam.

IT 279218-83-6P

(pos.-working photoresist composition for far UV ray exposure)

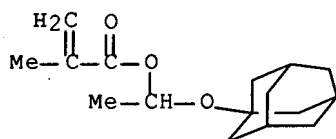
RN 279218-83-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, tetrahydro-4-methyl-2-oxo-2H-pyran-4-yl ester, polymer with 1-(tricyclo[3.3.1.1^{3,7}]dec-1-yloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 279218-82-5

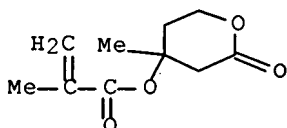
CMF C16 H24 O3



CM 2

CRN 177080-66-9

CMF C10 H14 O4



IC ICM G03F007-004
 ICS G03F007-039; H01L021-027
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 IT 177080-68-1P 181531-13-5P, 3-Oxocyclohexyl methacrylate-2-methyladamantyl methacrylate copolymer 279218-77-8P 279218-79-0P 279218-81-4P 279218-83-6P
 (pos.-working photoresist composition for far UV ray exposure)

L9 ANSWER 22 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1999:784819 HCAPLUS Full-text
 DOCUMENT NUMBER: 132:108372
 TITLE: Thermal dissociation behavior of polymers with hemiacetal ester moieties in the side chain: the effect of structure on dissociation temperature
 AUTHOR(S): Otsuka, Hideyuki; Fujiwara, Hirotada; Endo, Takeshi
 CORPORATE SOURCE: Research Laboratory of Resources Utilization, Tokyo Institute of Technology, Yokohama, 226-8503, Japan
 SOURCE: Journal of Polymer Science, Part A: Polymer Chemistry (1999), 37(24), 4478-4482
 CODEN: JPACEC; ISSN: 0887-624X
 PUBLISHER: John Wiley & Sons, Inc.
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 ED Entered STN: 12 Dec 1999

AB Polymers with hemiacetal ester structures in the side chain were prepared by radical polymerization of 1-alkoxypropyl and 1-alkoxyethyl methacrylates which in turn were prepared from the corresponding ethers and methacrylic acid in the presence of an acid catalyst. The radical polymerization was carried out using AIBN as initiator in chlorobenzene at 60° for 20 h. The thermal properties of the polymers were measured by thermogravimetry (TG) and DTA. Data indicate that thermal dissociation reactions of the hemiacetal ester moieties proceed via concerted mechanisms and are dependent on the mol. structure. Thus, thermally reactive polymers can be designed based on hemiacetal ester moieties.

IT 255716-78-0P
 (thermal dissociation of hemiacetal ester side chain moieties in polymethacrylates prepared by radical polymerization of alkoxyalkyl ether methacrylates)

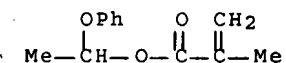
RN 255716-78-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-phenoxyethyl ester, homopolymer (9CI)
 (CA INDEX NAME)

CM 1

CRN 255716-77-9

CMF C12 H14 O3



CC 35-4 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 36

IT 138532-29-3P 140715-21-5P 143556-57-4P 215591-30-3P

255716-73-5P 255716-75-7P 255716-76-8P 255716-78-0P
255724-09-5P

(thermal dissociation of hemiacetal ester side chain moieties in polymethacrylates prepared by radical polymerization of alkoxyalkyl ether methacrylates)

REFERENCE COUNT: 29 THERE ARE 29 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L9 ANSWER 23 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1998:474170 HCAPLUS Full-text

DOCUMENT NUMBER: 129:231038

TITLE: Hemiacetal esterification of methacrylic acid

AUTHOR(S): Nakane, Yoshinori; Ishidoya, Masahiro; Endo, Takeshi

CORPORATE SOURCE: Coat. Res. Lab., NOF Corp., Yokohama, 244-0815, Japan

SOURCE: Nippon Setchaku Gakkaishi (1998), 34(7), 246-250

CODEN: NSEGE7; ISSN: 0916-4812

PUBLISHER: Nippon Setchaku Gakkai

DOCUMENT TYPE: Journal

LANGUAGE: Japanese

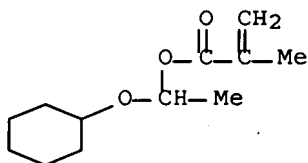
ED Entered STN: 30 Jul 1998

AB Hemiacetal esterification of methacrylic acid with alkyl vinyl ethers was carried out in order to prepare polymerizable monomers having protected carboxyl group. The esterification proceeded selectively in the presence of phosphoric acid without cationic polymerization of vinyl ethers and it was followed to the 2nd order. The reactivity of alkyl vinyl ethers followed to the order of: tert-Bu > cyclohexyl > iso-Pr > Et > Bu.

IT 143556-62-1P, 1-Cyclohexyloxyethyl methacrylate
(hemiacetal esterification of methacrylic acid by alkyl vinyl ethers)

RN 143556-62-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester (9CI) (CA INDEX NAME)



CC 35-2 (Chemistry of Synthetic High Polymers)
Section cross-reference(s): 23

IT 51920-52-6P, 1-Ethoxyethyl methacrylate 85997-75-7P, 1-Butoxyethyl methacrylate 143556-62-1P, 1-Cyclohexyloxyethyl methacrylate
212711-20-1P 212711-21-2P
(hemiacetal esterification of methacrylic acid by alkyl vinyl ethers)

L9 ANSWER 24 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1998:335156 HCAPLUS Full-text

DOCUMENT NUMBER: 129:47391

BERNSHTEYN 10/537,120

TITLE: Electrophotographic toner and its fixing method
 INVENTOR(S): Isobe, Kazuya; Kobayashi, Yoshiaki; Soeda, Kaori
 PATENT ASSIGNEE(S): Konica Co., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 3
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10133422	A	19980522	JP 1996-291592	19961101
			<--	
JP 3740759	B2	20060201		
US 5817443	A	19981006	US 1997-958307	19971027
			<--	
PRIORITY APPLN. INFO.:			JP 1996-288029	A 19961030
			<--	
			JP 1996-291592	A 19961101
			<--	
			JP 1997-67563	A 19970321
			<--	

ED Entered STN: 04 Jun 1998

AB The toner [storage modulus = 500-1200 and loss modulus = 1500-3000 dyn/cm² (at 160°)] comprises a colorant and a vinyl polymer. THF soluble component of the vinyl polymer has mol. weight peaks at 5000-15,000 and 300,000-400,000 in mol. weight distribution. The fixing method is also claimed, in which toner images obtained by the toner is fixed by a pressure and thermal fixing apparatus. The toner shows high hardness and images with smooth surface are obtained using less amount of oils.

IT 208173-58-4P

(crosslinked; electrophotog. developer toner containing ionomer vinyl polymer)

RN 208173-58-4 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with butyl 2-propenoate, 1,2-ethanediylbis[4,1-phenyleneoxy(1-methylethylidene)] bis(2-methyl-2-propenoate), ethenylbenzene and methyl 2-methyl-2-propenoate, zinc salt (9CI) (CA INDEX NAME)

CM 1

CRN 208173-57-3

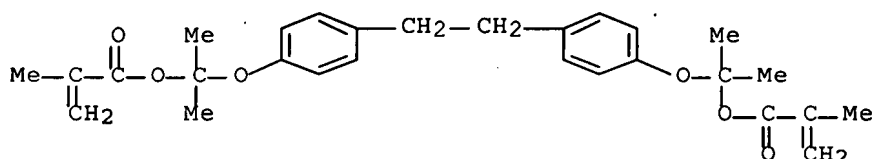
CMF (C28 H34 O6 . C10 H14 O6 . C8 H8 . C7 H12 O2 . C5 H8 O2)x

CCI PMS

CM 2

CRN 208173-56-2

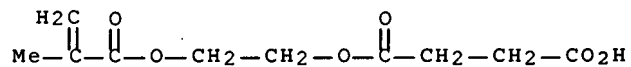
CMF C28 H34 O6



CM 3

CRN 20882-04-6

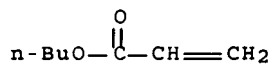
CMF C10 H14 O6



CM 4

CRN 141-32-2

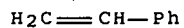
CMF C7 H12 O2



CM 5

CRN 100-42-5

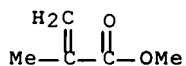
CMF C8 H8



CM 6

CRN 80-62-6

CMF C5 H8 O2



IC ICM G03G009-087

ICS G03G009-08; G03G009-09; G03G015-20

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 208173-58-4P

BERNSHTEYN 10/537,120

(crosslinked; electrophotog. developer toner containing ionomer vinyl polymer)

L9 ANSWER 25 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1998:197349 HCAPLUS Full-text
 DOCUMENT NUMBER: 128:263946
 TITLE: Novel polymers and photoresist compositions
 INVENTOR(S): Uday, Kumar
 PATENT ASSIGNEE(S): Shipley Co., LLC, USA
 SOURCE: Eur. Pat. Appl., 22 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 829766	A2	19980318	EP 1997-115532	19970908
			<--	
EP 829766	A3	19980701		
EP 829766	B1	20030212		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
US 6090526	A	20000718	US 1996-706138	19960913
			<--	
JP 2000029215	A	20000128	JP 1997-291498	19970916
			<--	

PRIORITY APPLN. INFO.: US 1996-706138 A 19960913
 <--

ED Entered STN: 06 Apr 1998

AB The present invention provides novel polymers and photoresist compns. that contain such polymers as binder components. The polymers of the invention include repeating units that contain acetalester or ketalester moieties. Preferred photoresists of the invention are chemical-amplified pos.-acting compns. that contain polymers with acetalester or ketalester moieties as binder components that can react to provide solubility differences in the presence of photochem. generated acids.

IT 205367-64-2P 205367-72-2P

(preparation and use in chemical amplified pos. photoresists)

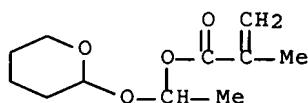
RN 205367-64-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, diphenylmethyl ester, polymer with 4-ethenylphenol and 1-[(tetrahydro-2H-pyran-2-yl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 205367-63-1

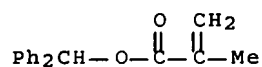
CMF C11 H18 O4



CM 2

CRN 25574-72-5

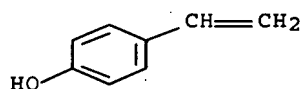
CMF C17 H16 O2



CM 3

CRN 2628-17-3

CMF C8 H8 O



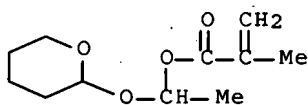
RN 205367-72-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(tetrahydro-2H-pyran-2-yl)oxy]ethyl ester, polymer with 4-ethenylphenol and exo-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 205367-63-1

CMF C11 H18 O4

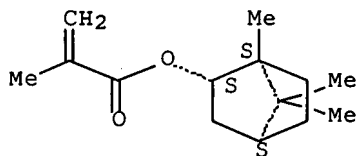


CM 2

CRN 7534-94-3

CMF C14 H22 O2

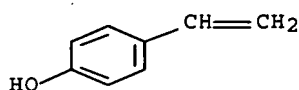
Relative stereochemistry.



CM 3

CRN 2628-17-3

CMF C8 H8 O



IC ICM G03F007-039

ICS C08F120-26

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 205367-41-5P, 4-Acetoxystyrene-isobornyl methacrylate-1-propyloxy-1-ethyl methacrylate copolymer 205367-45-9P 205367-49-3P
 205367-53-9P 205367-56-2P 205367-60-8P 205367-64-2P
 205367-66-4P 205367-68-6P 205367-72-2P

(preparation and use in chemical amplified pos. photoresists)

L9 ANSWER 26 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1997:594565 HCAPLUS Full-text

DOCUMENT NUMBER: 127:248875

TITLE: Polymers and photosensitive resin compositions
 using the same, and high-resolution heat-resistant
 pattern formation therefrom by far-UV lithography

INVENTOR(S): Iwasa, Shigeyuki; Maeda, Katsumi; Nakano,
 Kaichiro; Hasegawa, Etsuo

PATENT ASSIGNEE(S): NEC Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09221526	A	19970826	JP 1996-309742	19961120
			<--	
JP 2845225	B2	19990113		
US 5994025	A	19991130	US 1996-763054	19961210
			<--	
PRIORITY APPLN. INFO.:			JP 1995-322039	A 19951211
			<--	
			JP 1996-309742	A 19961120

<--

ED Entered STN: 17 Sep 1997

AB The title polymers are $[\text{CH}_2\text{C}(\text{R}_1)(\text{CO}_2\text{R}_2)]_x[\text{CH}_2\text{C}(\text{R}_3)(\text{CO}_2\text{C}(\text{R}_4)(\text{R}_5)(\text{OR}_6))]_y[\text{CH}_2\text{C}(\text{R}_7)(\text{CO}_2\text{H})]_z$ ($\text{R}_1, \text{R}_3, \text{R}_7 = \text{H}, \text{Me}; \text{R}_2 = \text{C}_7\text{-13}$ bridged cyclohydrocarbyl; $\text{R}_4 = \text{H}, \text{C}_1\text{-2}$ hydrocarbyl; $\text{R}_5 = \text{C}_1\text{-2}$ hydrocarbyl; $\text{R}_6 = \text{C}_1\text{-12}$ hydrocarbyl with or without 1-12 alkoxy or C1-13 acyl substituent; $x + y + z = 1$; $x = 0.1\text{-}0.9$; $y = 0.1\text{-}0.7$; $z = 0\text{-}0.7$) with Mw 1000-1,000,000 and used with photochem. acid generators for pattern making with light with wavelength 180-220 nm. Fancryl FA-513A, 1-ethoxyethyl methacrylate, and methacrylic acid were copolymd. in 5:3:2 molar ratio and the resulting copolymer was used with N-hydroxysuccinimide toluenesulfonate with line and space resolution 0.20 μm at exposure about 30 mJ/cm².

IT 195816-08-1P

(acrylic polymers and photosensitive resin compns. using the same, and high-resolution heat-resistant pattern formation therefrom by far-UV lithog.)

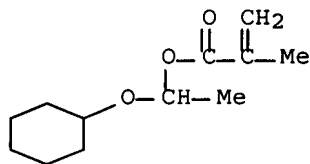
RN 195816-08-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and octahydro-4,7-methano-1H-inden-5-yl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

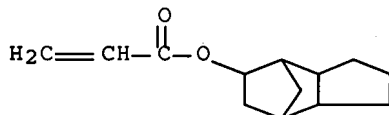
CMF C12 H20 O3



CM 2

CRN 7398-56-3

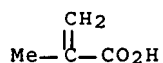
CMF C13 H18 O2



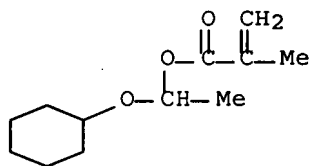
CM 3

CRN 79-41-4

CMF C4 H6 O2



IT 143556-62-1P, 1-Cyclohexyloxyethyl methacrylate
 (acrylic polymers and photosensitive resin compns. using the same,
 and high-resolution heat-resistant pattern formation therefrom by
 far-UV lithog.)
 RN 143556-62-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester (9CI) (CA
 INDEX NAME)



IC ICM C08F220-28
 ICS C08F220-06; C08F220-18; C09D133-14; G03F007-039; H01L021-027
 CC 37-6 (Plastics Manufacture and Processing)
 Section cross-reference(s): 74, 76
 IT 182073-92-3P 182073-93-4P 182073-94-5P 182073-95-6P
 182073-96-7P 195816-03-6P 195816-05-8P 195816-07-0P
 195816-08-1P 195816-10-5P 195816-12-7P 195816-14-9P
 (acrylic polymers and photosensitive resin compns. using the same,
 and high-resolution heat-resistant pattern formation therefrom by
 far-UV lithog.)
 IT 51920-52-6P, 1-Ethoxyethyl methacrylate 85997-75-7P, 1-Butoxyethyl
 methacrylate 143556-62-1P, 1-Cyclohexyloxyethyl methacrylate
 181894-78-0P, 1-(2-Methoxyethoxy)ethyl methacrylate 181894-79-1P
 181894-80-4P 181894-81-5P 195816-04-7P 195816-06-9P
 195816-09-2P, 1-(2-Ethoxyethoxy)ethyl methacrylate 195816-11-6P,
 1-(2-Butoxyethoxy)ethyl methacrylate 195816-13-8P,
 1-(2-Butyryloxyethoxy)ethyl methacrylate
 (acrylic polymers and photosensitive resin compns. using the same,
 and high-resolution heat-resistant pattern formation therefrom by
 far-UV lithog.)

L9 ANSWER 27 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1996:476703 HCAPLUS Full-text
 DOCUMENT NUMBER: 125:117552
 TITLE: Hydrolyzable self-polishing coating composition
 INVENTOR(S): Matsubara, Yoshiro; Itoh, Masayasu; Ishidoya,
 Masahiro; Honda, Yoshihiro
 PATENT ASSIGNEE(S): Nof Corporation, Japan
 SOURCE: Eur. Pat. Appl., 25 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

BERNSHTEYN 10/537,120

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 714957	A1	19960605	EP 1995-118255	19951120
<--				
EP 714957	B1	19980304		
R: BE, DE, DK, GB, GR, IT, NL, SE				
JP 08199095	A	19960806	JP 1995-272777	19951020
<--				
JP 3396349	B2	20030414		
US 5767171	A	19980616	US 1995-560028	19951117
<--				
FI 9505588	A	19960522	FI 1995-5588	19951120
<--				
FI 108042	B1	20011115		
NO 9504675	A	19960522	NO 1995-4675	19951120
<--				
NO 309486	B1	20010205		
KR 189477	B1	19990601	KR 1995-42169	19951120
<--				
CN 1128778	A	19960814	CN 1995-119618	19951121
<--				
CN 1058280	B	20001108		
PRIORITY APPLN. INFO.:			JP 1994-312675	A 19941121
<--				

ED Entered STN: 13 Aug 1996

AB A hydrolyzable self-polishing coating composition for use in preventing attachment of organisms to the surface of structures submerged in seawater, which comprises an antifoulant and a copolymer of an organosilyl group-containing monomer and a hemiacetal ester group-containing monomer. Thus, 50 parts Et vinyl ether was treated with 50 parts acrylic acid to give ethoxyethyl acrylate, which (14.417 parts) was radically polymerized with 40.572 parts tributylsilyl acrylate and 45.011 parts Me methacrylate and used to prepare a coating material.

IT 179630-35-4P

(hydrolyzable self-polishing coating materials containing antifouling agents)

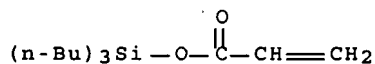
RN 179630-35-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 1-(cyclohexyloxy)ethyl 2-propenoate and tributylsilyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 179630-31-0

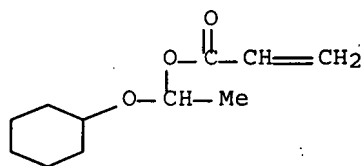
CMF C15 H30 O2 Si



CM 2

CRN 153206-78-1

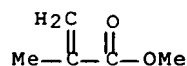
CMF C11 H18 O3



CM 3

CRN 80-62-6

CMF C5 H8 O2



IC ICM C09D005-16

ICS C09D143-04

CC 42-10 (Coatings, Inks, and Related Products)

IT 179630-32-1P 179630-34-3P 179630-35-4P 179630-37-6P

179630-38-7P 179630-39-8P 179630-40-1P 179630-41-2P

179630-44-5P 179630-47-8P

(hydrolyzable self-polishing coating materials containing antifouling agents)

L9 ANSWER 28 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1995:849678 HCAPLUS Full-text

DOCUMENT NUMBER: 124:179019

TITLE: Thermosetting powdered acrylic polymer coating compositions

INVENTOR(S): Mashita, Mitsuyuki; Kawashima, Tatsuo

PATENT ASSIGNEE(S): Nippon Oils & Fats Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07196951	A	19950801	JP 1993-349084	19931228
			<--	
JP 3277663	B2	20020422		
PRIORITY APPLN. INFO.:			JP 1993-349084	19931228
			<--	

ED Entered STN: 12 Oct 1995

AB Coatings with a smooth surface are prepared from vinyl polymers with glass-transition temperature (Tg) 40-150° and weight-average mol. weight (Mw) 2000-50,000 comprising 5-80% CR1R2CR3(CO2CHR4YR5) units (R1-R3 = H, C1-18 organic group; R4 = C1-18 organic group; R5 = C≥5 organic group; or CHR4YR5 may form a

BERNSHTEYN 10/537,120

6- or higher-membered heterocyclic group with Y as hetero atom; Y = O, S) and 20-95% other vinyl monomer-derived units. Thus, 169.8:152.1:78.1 1-(cyclohexyloxy)ethyl methacrylate-cyclohexyl methacrylate-Bu methacrylate copolymer (Tg 60°, Mw 11,300) 1000, triglycidyl isocyanurate 198, Tinuvin 900 10, Sanol LS 440 10, Resimix RL 4 5, and benzoin 5 parts were mixed, melt-kneaded, and pulverized to give title powdered composition showing good blocking resistance, which was electrostatically coated onto a steel plate and baked to give a test piece of smooth surface, good adhesion, and solvent resistance.

IT 171664-19-0P 171664-20-3P 172274-36-1P
172519-70-9P 172519-71-0P

(thermosetting vinyl polymer powder coatings with smooth surface)

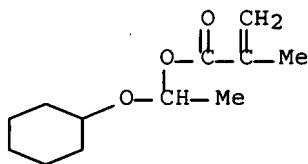
RN 171664-19-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with cyclohexyl 2-methyl-2-propenoate, 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and 1,3,5-tris(oxiranylmethyl)-1,3,5-triazine-2,4,6(1H,3H,5H)-trione (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

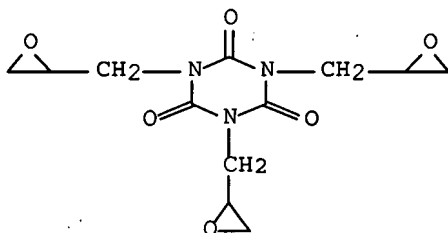
CMF C12 H20 O3



CM 2

CRN 2451-62-9

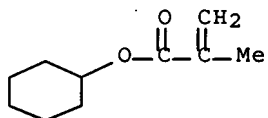
CMF C12 H15 N3 O6



CM 3

CRN 101-43-9

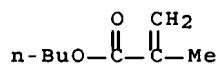
CMF C10 H16 O2



CM 4

CRN 97-88-1

CMF C8 H14 O2



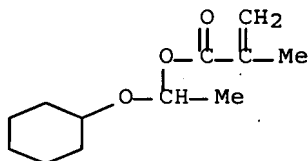
RN 171664-20-3 HCAPLUS

CN 1,4-Benzenedicarboxylic acid, bis(oxiranylmethyl) ester, polymer with butyl 2-methyl-2-propenoate, 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

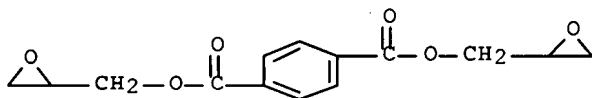
CMF C12 H20 O3



CM 2

CRN 7195-44-0

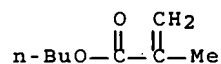
CMF C14 H14 O6



CM 3

CRN 97-88-1

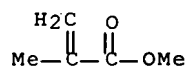
CMF C8 H14 O2



CM 4

CRN 80-62-6

CMF C5 H8 O2



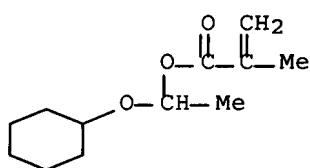
RN 172274-36-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate, decahydro-1,4:5,8-
dimethanonaphthalenyl 2-propenoate, methyl 2-methyl-2-propenoate and
1,3,5-tris(oxiranylmethyl)-1,3,5-triazine-2,4,6(1H,3H,5H)-trione (9CI)
(CA INDEX NAME)

CM 1

CRN 143556-62-1

CMF C12 H20 O3

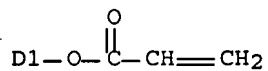
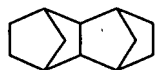


CM 2

CRN 141550-78-9

CMF C15 H20 O2

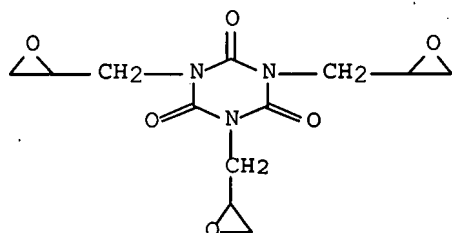
CCI IDS



CM 3

CRN 2451-62-9

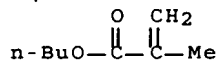
CMF C12 H15 N3 O6



CM 4

CRN 97-88-1

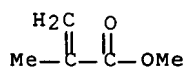
CMF C8 H14 O2



CM 5

CRN 80-62-6

CMF C5 H8 O2



RN 172519-70-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate, ethenylbenzene, methyl

BERNSHTEYN 10/537,120

2-methyl-2-propenoate and Primid XL 122 (9CI) (CA INDEX NAME)

CM 1

CRN 172306-18-2

CMF Unspecified

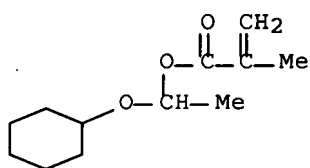
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 143556-62-1

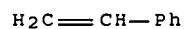
CMF C12 H20 O3



CM 3

CRN 100-42-5

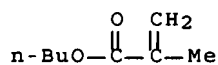
CMF C8 H8



CM 4

CRN 97-88-1

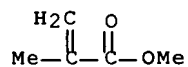
CMF C8 H14 O2



CM 5

CRN 80-62-6

CMF C5 H8 O2



RN 172519-71-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with BF 1065,
cyclohexyl 2-methyl-2-propenoate, 1-(cyclohexyloxy)ethyl
2-methyl-2-propenoate, decahydro-1,4:5,8-dimethanonaphthalenyl
2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and Primid XL 122
(9CI) (CA INDEX NAME)

CM 1

CRN 172306-18-2

CMF Unspecified

CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 171263-93-7

CMF Unspecified

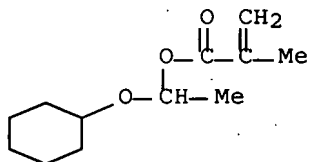
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 143556-62-1

CMF C12 H20 O3

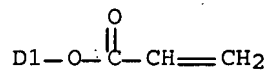
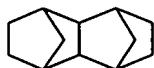


CM 4

CRN 141550-78-9

CMF C15 H20 O2

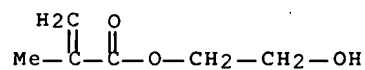
CCI IDS



CM 5

CRN 868-77-9

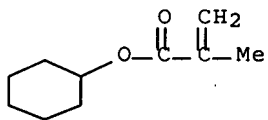
CMF C6 H10 O3



CM 6

CRN 101-43-9

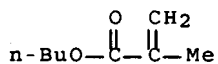
CMF C10 H16 O2



CM 7

CRN 97-88-1

CMF C8 H14 O2



IC ICM C09D005-03
ICS C09D133-04
CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 55
IT 171664-19-0P 171664-20-3P 171664-21-4P
172274-36-1P 172304-08-4P 172519-70-9P
172519-71-0P

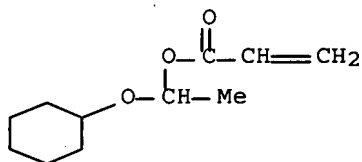
BERNSHTEYN 10/537,120

(thermosetting vinyl polymer powder coatings with smooth surface)

L9 ANSWER 29 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1994:701570 HCAPLUS Full-text
 DOCUMENT NUMBER: 121:301570
 TITLE: Manufacture of hemiacetal esters
 INVENTOR(S): Yamamura, Kazuo; Oooka, Masataka
 PATENT ASSIGNEE(S): Dainippon Ink & Chemicals, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 06135877	A	19940517	JP 1992-210236	19920806
			<--	
PRIORITY APPLN. INFO.:			JP 1992-210236	19920806
			<--	

OTHER SOURCE(S): MARPAT 121:301570
 ED Entered STN: 24 Dec 1994
 AB The title esters having CO₂CHMeOZ group (Z = organic group) are prepared by addition reaction of vinyl ethers CH₂:CHOZ and ethylenically unsatd. carboxylic acids other than methacrylic acid in the presence of an acid halide catalyst. 1-Butoxyethyl acrylate was prepared in 81% yield from acrylic acid and Bu vinyl ether in the presence of acryloyl chloride.
 IT 153206-78-1P
 (manufacture of)
 RN 153206-78-1 HCAPLUS
 CN 2-Propenoic acid, 1-(cyclohexyloxy)ethyl ester (9CI) (CA INDEX NAME)



IC ICM C07C043-30
 ICS C07C069-653
 CC 35-2 (Chemistry of Synthetic High Polymers)
 Section cross-reference(s): 23
 IT 77-99-6DP, Trimethylolpropane, reaction products with caprolactone and Et vinyl ether 502-44-3DP, ε-Caprolactone, reaction products with trimethylolpropane and Et vinyl ether 52858-59-0P 86164-66-1P 90646-92-7P 153206-78-1P
 (manufacture of)

L9 ANSWER 30 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1994:109600 HCAPLUS Full-text
 DOCUMENT NUMBER: 120:109600
 TITLE: Hemiacetal or hemiketal ester-protected functional group-containing vinyl polymers for coatings

. BERNSHTEYN 10/537,120

INVENTOR(S): Azuma, Ichiro; Iwamura, Goro; Takezawa, Shoichiro;
 Oooka, Masataka; Yamamura, Kazuo
 PATENT ASSIGNEE(S): Dainippon Ink & Chemicals, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 30 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05186739	A	19930727	JP 1992-3841	19920113

PRIORITY APPLN. INFO.: JP 1992-3841 19920113
 <--

ED Entered STN: 05 Mar 1994

AB Storage-stable, acid- and scratch-resistant coatings contain title polymers, polymers containing ≥ 2 epoxy groups, and OH-reactive hardeners. A composition containing Super-Beckamine L 117, Bu acrylate (I)-Bu methacrylate (II)-glycidyl methacrylate-styrene (III) copolymer, and I-II-III-1-(iso-butoxy)ethyl methacrylate showed good storage stability at 40° for 20 days.

IT 152330-05-7P

(preparation of, coatings containing, storage-stable)

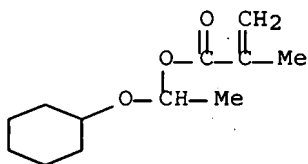
RN 152330-05-7 HCAPLUS

CN 2-Propenoic acid, methoxy-, 3-(trimethoxysilyl)propyl ester, polymer with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

CMF C12 H20 O3

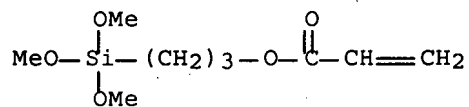


CM 2

CRN 34215-73-1

CMF C10 H20 O6 Si

CCI IDS

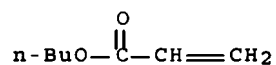


D1-O-Me

CM 3

CRN 141-32-2

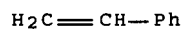
CMF C7 H12 O2



CM 4

CRN 100-42-5

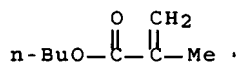
CMF C8 H8



CM 5

CRN 97-88-1

CMF C8 H14 O2



IC ICM C09D163-00
ICS B05D001-36; B05D007-24; C09D161-20; C09D175-04; C09D201-06
ICA C08G059-40
CC 42-10 (Coatings, Inks, and Related Products)
IT 152330-04-6P 152330-05-7P 152330-06-8P 152330-07-9P
152381-90-3P
(preparation of, coatings containing, storage-stable)

L9 ANSWER 31 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 1994:56812 HCAPLUS Full-text
DOCUMENT NUMBER: 120:56812

BERNSHTEYN 10/537,120

TITLE: Foamable thermosetting powder coating compositions
and coated products using the same
INVENTOR(S): Matsubara, Yoshiro; Mashita, Mitsuyuki
PATENT ASSIGNEE(S): Nippon Oils & Fats Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05148430	A	19930615	JP 1991-337761	19911127

PRIORITY APPLN. INFO.: JP 1991-337761 19911127
<--

ED Entered STN: 05 Feb 1994

AB The title compns. providing coatings with heat and sound insulation (no data) contain a vinyl copolymer (Tg 40-150°, Mw 2000-50,000) from 5-80% R1R2C:CR3(R4)kCO2CR5(CHR6R7)(YR8) (I, R1-7 = H, C1-18 organic group; R8 = C1-18 organic group; R7 and R8 could be ring member with Y as heteroatom; Y = O, S; k = 0, 1) and 95-20% other vinyl monomer and 0.5-2.0 mol (based on I) solid compound containing ≥2 epoxy groups. A powdered copolymer (Tg 59.9°, Mw 7500) prepared from 1-ethoxyethyl methacrylate 31.6, Me methacrylate 52.4, and Bu methacrylate 16 parts in the presence of AIBN and lauryl mercaptan was mixed 78.2:21.8 with diglycidyl terephthalate, electrostatically coated on tinplate, and baked at 160° for 30 min to give a foamed coating with expansion ratio 2.5-3.0 with good solvent and water resistance.

IT 152313-23-0P
(manufacture of, for foamable solvent- and water-resistant powder coatings)

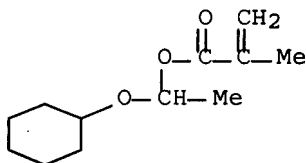
RN 152313-23-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and 1,3,5-tris(oxiranylmethyl)-1,3,5-triazine-2,4,6(1H,3H,5H)-trione (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

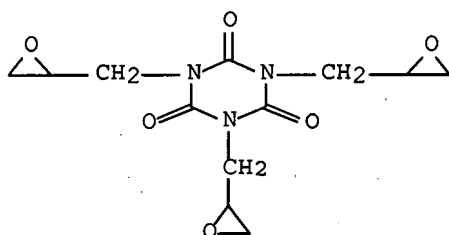
CMF C12 H20 O3



CM 2

CRN 2451-62-9

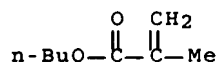
CMF C12 H15 N3 O6



CM 3

CRN 97-88-1

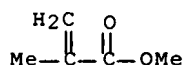
CMF C8 H14 O2



CM 4

CRN 80-62-6

CMF C5 H8 O2



IC ICM C09D005-03

ICS C09D005-00; C09D005-03; C09D133-14; C09D163-00

CC 42-10 (Coatings, Inks, and Related Products)

IT 152313-22-9P 152313-23-0P 152313-24-1P 152313-25-2P

(manufacture of, for foamable solvent- and water-resistant powder coatings)

L9 ANSWER 32 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1994:56811 HCAPLUS Full-text

DOCUMENT NUMBER: 120:56811

TITLE: Foamable thermosetting powder coating compositions and coated products using the same

INVENTOR(S): Mashita, Mitsuyuki; Matsubara, Yoshiro; Kawashima, Tatsuo

PATENT ASSIGNEE(S): Nippon Oils & Fats Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05148429	A	19930615	JP 1991-336122	19911126

PRIORITY APPLN. INFO.:

JP 1991-336122 19911126

ED Entered STN: 05 Feb 1994

AB The title compns. providing coatings with heat and sound insulation (no data) contain a vinyl copolymer or blend with Tg 40-150° and Mw 2000-50,000, wherein the vinyl copolymer is from 5-80% R1R2C:CR3(R4)kCO2CR5(CHR6R7)(YR8) (R1-7 = H, C1-18 organic group; R8 = C1-18 organic group; R7 and R8 could be ring member with Y as heteroatom; Y = O, S; k = 0, 1), 0.5-2.0 mol (based on the above monomer) glycidyl group-containing vinyl monomer and/or β-hydroxyalkylamide group-containing vinyl monomer, and other vinyl monomer. A powdered copolymer (Tg 60°, Mw 14,500) prepared from 1-ethoxyethyl methacrylate 31.6, tetracyclododecyl acrylate 35.4, cyclohexyl methacrylate 4.6, and glycidyl methacrylate 28.4 parts in the presence of AIBN was classified (150 mesh), electrostatically coated on tinplate, and baked at 160° for 30 min to give a foamed coating with expansion ratio 2.5-3.0 with good solvent and water resistance.

IT 152188-84-6P

(manufacture of, for foamable thermosetting powder coatings with good solvent and water resistance)

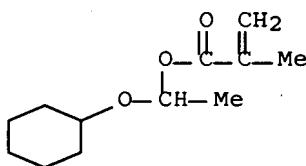
RN 152188-84-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with cyclohexyl 2-methyl-2-propenoate, 1-(cyclohexyloxy)ethyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

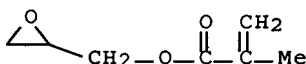
CMF C12 H20 O3



CM 2

CRN 106-91-2

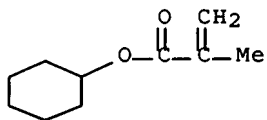
CMF C7 H10 O3



CM 3

CRN 101-43-9

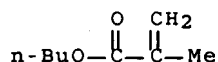
CMF C10 H16 O2



CM 4

CRN 97-88-1

CMF C8 H14 O2



IC ICM C09D005-03
 ICS C09D005-00; C09D129-10; C09D133-14
 CC 42-10 (Coatings, Inks, and Related Products)
 IT 79-10-7DP, Acrylic acid, tetracyclododecyl esters, acrylic copolymers
 101-43-9DP, Cyclohexyl methacrylate, acrylic copolymers 106-91-2DP,
 Glycidyl methacrylate, acrylic copolymers 51920-52-6DP, acrylic
 copolymers 52858-59-0DP, Tetrahydropyranyl methacrylate, acrylic
 copolymers 138554-09-3DP, 1-Isobutoxyethyl methacrylate, acrylic
 copolymers 151486-00-9DP, acrylic copolymers 152121-14-7P
 152188-84-6P
 (manufacture of, for foamable thermosetting powder coatings with good
 solvent and water resistance)

L9 ANSWER 33 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1993:255506 HCAPLUS Full-text

DOCUMENT NUMBER: 118:255506

TITLE: Preparation of 1-substituted ethyl methacrylate

INVENTOR(S): Yamamura, Kazuo; Ooka, Masataka

PATENT ASSIGNEE(S): Dainippon Ink and Chemicals, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 04279609	A	19921005	JP 1991-151671	19910624

JP 3180818 B2 20010625 <--
 PRIORITY APPLN. INFO.: JP 1990-203717 A1 19900731
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OTHER SOURCE(S): MARPAT 118:255506

ED Entered STN: 26 Jun 1993

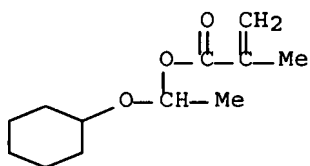
AB The title compds. $\text{H}_2\text{C}:\text{CMeCOOCHMe}(\text{OZ})$ ($\text{Z} = \text{C}_3\text{-18 alkyl, C}_1\text{-18 substituted alkyl, cyclopentyl, cyclohexyl, aromatic group}$) are prepared by reacting methacrylic acid (I) with $\text{H}_2\text{C}:\text{CH}(\text{OZ})$. Thus, adding 100 g Bu vinyl ether to a mixture of I 80, methacryloyl chloride 0.6, and phenothiazine 0.1 g dropwise at 40° over 30 min, and heating at 50° for 4 h gave 81% 1-butoxy-1-ethyl methacrylate.

IT 143556-62-1P

(preparation of)

RN 143556-62-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester (9CI) (CA INDEX NAME)



IC ICM C08F020-28

ICS C07C067-04; C07C069-54

CC 35-2 (Chemistry of Synthetic High Polymers)

IT 85997-75-7P 143556-62-1P 147898-28-0P

(preparation of)

L9 ANSWER 34 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1992:551623 HCAPLUS Full-text

DOCUMENT NUMBER: 117:151623

TITLE: Vinyl polymers with hemiacetal or hemiketal ester side chains

INVENTOR(S): Iwamura, Goro; Yamamura, Kazuo; Ooka, Masataka

PATENT ASSIGNEE(S): Dainippon Ink and Chemicals, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 04103605	A	19920406	JP 1990-222186	19900823

<--

PRIORITY APPLN. INFO.: JP 1990-222186 19900823

<--

ED Entered STN: 17 Oct 1992

AB The title polymers have side chains CO_2R_1 ($\text{R}_1 = \text{oxacycloalkyl or 1-alkoxy-1-cycloalkyl}$) or $\text{CO}_2\text{CH}(\text{OR}_3)\text{CH}_2\text{R}_2$ [$\text{R}_2 = \text{H, C}_1\text{-10 alkyl; R}_3 = (\text{un})\text{substituted C}_1\text{-22 alkyl}$] in 0.1-100% of the repeating units. Thus, 2-

(methacryloyloxy)tetrahydrofuran was polymerized in PhMe in the presence of 0.2% tert-Bu peroctoate at 100° to give a polymer having number-average mol. weight 100,000, acid value ≤0.1, and good stability.

IT 143556-63-2P

(preparation of, with long-term stability)

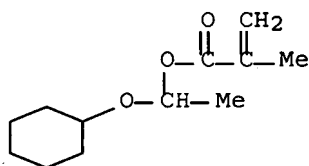
RN 143556-63-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester, polymer with butyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 143556-62-1

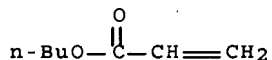
CMF C12 H20 O3



CM 2

CRN 141-32-2

CMF C7 H12 O2



IC ICM C08F020-28

ICS C08F016-18; C08F018-04; C08F020-30; C08F022-20; C08F214-24; C08F246-00

CC 35-4 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 37

IT 39612-01-6P 143556-56-3P 143556-57-4P 143556-59-6P

143556-61-0P 143556-63-2P 143556-65-4P 143684-67-7P

143684-68-8P

(preparation of, with long-term stability)

L9 ANSWER 35 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1991:160680 HCAPLUS Full-text

DOCUMENT NUMBER: 114:160680

TITLE: Caffeoylmalic and two pyrrole acids from *Parietaria officinalis*

AUTHOR(S): Budzianowski, Jaromir

CORPORATE SOURCE: Dep. Pharm. Bot., K. Marcinkowski Med. Acad., Poznan, 61-712, Pol.

SOURCE: Phytochemistry (1990), 29(10), 3299-301

CODEN: PYTCAS; ISSN: 0031-9422

DOCUMENT TYPE: Journal

Oc1cc(O)ccc1C=CC(=O)OCC(=O)Nc2cc(C(=O)O)c(C)c2C(=O)O CO_2H

```
L9      ANSWER 36 OF 48      HCAPLUS  COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER:           1991:25544  HCAPLUS  Full-text
DOCUMENT NUMBER:            114:25544
TITLE:                      Anaerobic adhesive compositions
INVENTOR(S):                Haruna, Katsunori; Okuma, Atsushi
PATENT ASSIGNEE(S):         Three Bond Co., Ltd., Japan
SOURCE:                     Jpn. Kokai Tokkyo Koho, 7 pp.
                                CODEN: JKXXAF
DOCUMENT TYPE:               Patent
LANGUAGE:                    Japanese
FAMILY ACC. NUM. COUNT:     1
```

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 02187401	A	19900723	JP 1989-8066	19890117

PRIORITY APPLN. INFO.:

JP 1989-8066

19890117

ED Entered STN: 26 Jan 1991

AB Title compns., room temperature-curable and useful for fastening bolts and nuts, comprise ethylenic double bond-terminated monomers, polymerization initiators, and heterocyclic compds. containing imidazole, 2H-1,3-dioxole, and/or 2H,5H-1,2,5-oxadiazole rings or their isomers in their structure. Thus, a mixture of 2-hydroxy-1-phenoxyethyl acrylate 20, isobornyl methacrylate 20, GMN-U (polyurethane acrylate) 40, 2-hydroxyethyl methacrylate 20, EDTA di-Na salt 0.02, cumene hydroperoxide 0.5, n-dodecyl mercaptan 0.2, and 2-mercaptobenzimidazole (I) 1.0 part was applied to an Fe bolt, screwed into an Fe nut, and allowed to cure until unloosenable by hand. The set time was 100 s vs. ≥ 24 h without I or 120 s with o-benzoic sulfimide in place of I.

IT 122280-44-8P

(preparation of, as room temperature-cured anaerobic adhesives for fastening

bolts and nuts, catalysts for)

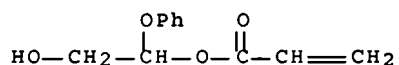
RN 122280-44-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with GMN-U, 2-hydroxy-1-phenoxyethyl 2-propenoate and exo-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 122280-43-7

CMF C11 H12 O4



CM . 2

CRN 122157-62-4

CMF Unspecified

CCI PMS, MAN

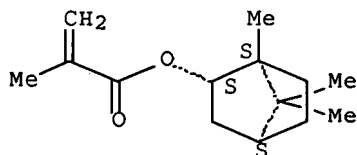
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 7534-94-3

CMF C14 H22 O2

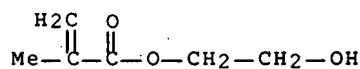
Relative stereochemistry.



CM 4

CRN 868-77-9

CMF C6 H10 O3



IC ICM C08F002-38
ICS C08F004-00; C09J004-00
CC 38-3 (Plastics Fabrication and Uses)
Section cross-reference(s): 37
IT 80-05-7DP, Bisphenol A, derivs., methacrylate, polymers with
hydroxyethyl methacrylate 868-77-9DP, 2-Hydroxyethyl methacrylate,
polymers with bisphenol A-type methacrylates 122280-44-8P
(preparation of, as room temperature-cured anaerobic adhesives for
fastening
bolts and nuts, catalysts for)

L9 ANSWER 37 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1988:204409 HCAPLUS Full-text

DOCUMENT NUMBER: 108:204409

TITLE: Preparation of 6-(substituted methylene)penem
antibacterials by novel routesINVENTOR(S): Coulton, Steven; Harbridge, John Barry; Osborne,
Neal Frederick; Walker, Graham

PATENT ASSIGNEE(S): Beecham Group PLC, UK

SOURCE: Eur. Pat. Appl., 68 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

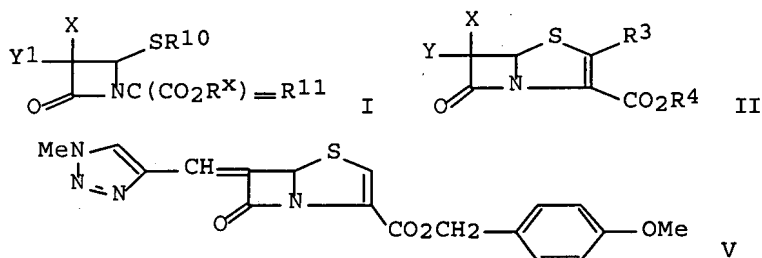
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 232966	A1	19870819	EP 1987-300193	19870109
			<--	
EP 232966	B1	19971008		
R: AT, BE, CH, DE, ES, FR, GB, GR, IT, LI, LU, NL, SE				
AT 159021	T	19971015	AT 1987-300193	19870109
			<--	
DK 8700212	A	19870718	DK 1987-212	19870115
			<--	
NO 8700176	A	19870720	NO 1987-176	19870115

BERNSHTEYN 10/537,120

AU 8767586	A	19870723	AU 1987-67586	19870115
			<--	
AU 607693	B2	19910314		
ZA 8700273	A	19871230	ZA 1987-273	19870115
			<--	
HU 45260	A2	19880628	HU 1987-114	19870115
			<--	
HU 198725	B	19891128		
FI 8700176	A	19870718	FI 1987-176	19870116
			<--	
JP 62169792	A	19870725	JP 1987-8854	19870116
			<--	
JP 07098822	B	19951025		
AU 9178267	A	19910829	AU 1991-78267	19910611
			<--	
AU 9178268	A	19910829	AU 1991-78268	19910611
			<--	
JP 08291139	A	19961105	JP 1995-139794	19950418
			<--	
PRIORITY APPLN. INFO.:			GB 1986-1119	A 19860117
			<--	
			GB 1986-25017	A 19861018
			<--	

OTHER SOURCE(S): MARPAT 108:204409
 ED Entered STN: 11 Jun 1988
 GI



AB Azetidinones I [Rx = carboxy protective group; R10 = H, (un)substituted ammonium ion, organothio group, metal ion, CR3:R13; R11 = O, 1-methylethylidene, phosphoranylidene; R3 = H, organic group; R13 = O, S, CHR14; R14 = H, organic group; X = halo; Y1 = H, halo] were prepared and converted to penems II [R3 = H, organic group; R4 = H, ion, ester residue; X = halo; Y = H, halo, CHZR12; R12 = H, (un)substituted hydrocarbyl, heterocyclyl; Z = halo, (un)substituted OH, SOnR5, SeOmR5; R5 = H, hydrocarbyl, heterocyclyl; n = 0-2; m = 0, 1] which, in turn, were converted to antibacterial agents II (XY = CHR12) (III). 4-Methoxybenzyl 6-bromopenicillanate 1-oxide and HC.tplbond.CCO2CH2CCl3 were refluxed in PhMe and the product treated with PBr3 to give I [R10 = (E)-CH:CHCO2CH2CCl3, R11 = CMe2, Rx = 4-MeOC6H4CH2, X = Br, Y1 = H] which was ozonized followed by treatment with (MeO)3P to give II (R3 = Y = H, R4 = 4-MeOC6H4CH2, X = Br) (IV). The latter was stirred with (Me3Si)2NLi followed by 1-methyl-1,2,3-triazole-4-carboxaldehyde to give II [Y = (1-methyl-1,2,3-triazol-4-yl)hydroxymethyl] which was treated with Ac2O

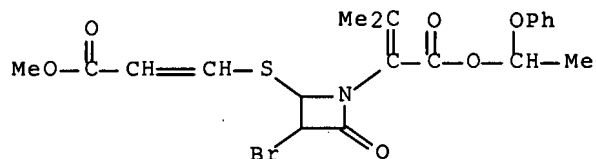
followed by Zn/HOAc to give (triazolylmethylene)penemcarboxylate (Z)-V and a small amount of the (E)-isomer.

IT 114408-67-2P

(preparation and reaction of, in preparation of antibacterial agents)

RN 114408-67-2 HCAPLUS

CN 1-Azetidineacetic acid, 3-bromo-2-[(3-methoxy-3-oxo-1-propenyl)thio]-
 α -(1-methylethylidene)-4-oxo-, 1-phenoxyethyl ester (9CI) (CA
 INDEX NAME)



IC ICM C07D499-00

ICS C07F009-65; C07D205-08

ICA C07D417-12

CC 26-5 (Biomolecules and Their Synthetic Analogs)

Section cross-reference(s): 1

IT 76631-83-9P 94134-57-3P 96572-55-3P 102991-08-2P 114408-47-8P
 114408-66-1P 114408-67-2P 114408-83-2P 114408-92-3P
 114408-93-4P 114408-95-6P 114408-96-7P 114408-97-8P
 114408-98-9P 114408-99-0P 114409-12-0P 114409-13-1P
 114409-14-2P 114409-15-3P 114409-17-5P 114409-18-6P
 114409-19-7P 114409-20-0P 114409-22-2P 114409-23-3P
 114409-24-4P 114409-25-5P 114409-26-6P 114409-27-7P
 114429-78-6P 114429-79-7P 114429-80-0P 114429-81-1P
 114429-82-2P 114429-83-3P 114429-84-4P 114488-60-7P
 114488-61-8P

(preparation and reaction of, in preparation of antibacterial agents)

L9 ANSWER 38 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1988:151009 HCAPLUS Full-text

DOCUMENT NUMBER: 108:151009

TITLE: Initiation mechanisms in radical polymerization:
 reaction of tert-butoxy radicals with allyl
 acrylate and with diallyl ether

AUTHOR(S): Busfield, W. Ken; Jenkins, Ian D.; Thang, San H.;
 Rizzardo, Ezio; Solomon, David H.

CORPORATE SOURCE: Sch. Sci., Griffith Univ., Nathan, 4111, Australia

SOURCE: Journal of the Chemical Society, Perkin
 Transactions 1: Organic and Bio-Organic Chemistry
 (1972-1999) (1988), (3), 485-90
 CODEN: JCPRB4; ISSN: 0300-922X

DOCUMENT TYPE: Journal

LANGUAGE: English

ED Entered STN: 30 Apr 1988

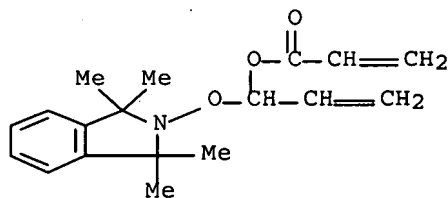
AB The radical trapping technique employing 1,1,3,3-tetramethyl-1,3-dihydroisindol-2-yloxyl as a scavenger was used to study the reaction of tert-butoxy radicals with allyl acrylate and with diallyl ether. With allyl acrylate, extensive H abstraction as well as addition to both allyl and acryloyl double bonds were observed, whereas with diallyl ether, the only products obtained were derived exclusively from H abstraction.

IT 113694-93-2P

(preparation of)

RN 113694-93-2 HCAPLUS

CN 2-Propenoic acid, 1-[(1,3-dihydro-1,1,3,3-tetramethyl-2H-isoindol-2-yl)oxy]-2-propenyl ester (9CI) (CA INDEX NAME)



CC 35-3 (Chemistry of Synthetic High Polymers)

IT 89429-39-0P 113694-89-6P 113694-90-9P 113694-91-0P

113694-92-1P 113694-93-2P 113694-94-3P 113694-95-4P

113694-96-5P 113694-97-6P 113694-98-7P

(preparation of)

L9 ANSWER 39 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1985:437788 HCAPLUS Full-text

DOCUMENT NUMBER: 103:37788

TITLE: Initiation mechanisms in radical polymerization:
reaction of tert-butoxy radicals with allyl
methacrylateAUTHOR(S): Busfield, W. Ken; Jenkins, Ian D.; Thang, San H.;
Rizzardo, Ezio; Solomon, David H.

CORPORATE SOURCE: Sch. Sci., Griffith Univ., Nathan, 4111, Australia

SOURCE: Australian Journal of Chemistry (1985),

38(5), 689-98

CODEN: AJCHAS; ISSN: 0004-9425

DOCUMENT TYPE: Journal

LANGUAGE: English

ED Entered STN: 10 Aug 1985

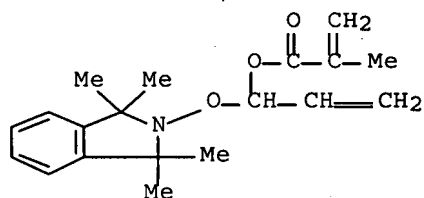
AB The radical-trapping technique employing 1,1,3,3-tetramethylisoindolin-2-ylloxyl [80037-90-7] as scavenger has been used to study the reactions of tert-BuO radical [3141-58-0] (prepared from bis(tert-Bu peroxalate) allyl methacrylate [96-05-9]. Extensive H abstraction as well as addition to both allyl and acryloyl double bonds was observed. One unusual feature of the reaction, the formation of considerably more (Z)-alkene than (E)-alkene from trapping of radicals derived from the allyloxy moiety, is also discussed.

IT 96990-79-3P

(formation of, in reactions of allyl methacrylate with tert-butoxyl radicals, in presence isoindolinyl oxy scavenger)

RN 96990-79-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-[(1,3-dihydro-1,1,3,3-tetramethyl-2H-isoindol-2-yl)oxy]-2-propenyl ester (9CI) (CA INDEX NAME)



CC 35-4 (Chemistry of Synthetic High Polymers)

Section cross-reference(s): 22, 27

IT 80037-95-2P 96990-79-3P 96990-80-6P 96990-81-7P

96990-82-8P 96990-83-9P 96990-84-0P 96990-85-1P 96990-86-2P

96990-87-3P 97184-51-5P

(formation of, in reactions of allyl methacrylate with tert-butoxyl radicals, in presence isoindolinyl oxy scavenger)

L9 ANSWER 40 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1985:24330 HCAPLUS Full-text

DOCUMENT NUMBER: 102:24330

TITLE: 1-Phenoxyethyl esters, a new family of carboxy
protective groups

AUTHOR(S) : Alpegiani, Marco; Bedeschi, Angelo; Foglio, Maurizio; Perrone, Ettore

CORPORATE SOURCE: Ric. Sviluppo Chim., Farmitalia Carlo Erba S.p.A.,
Milan, Italy

SOURCE: Gazzetta Chimica Italiana (1984),
114(7-8), 391-3

CODEN: GCITA9; ISSN: 0016-5603

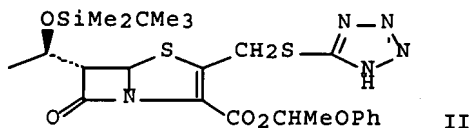
DOCUMENT TYPE: Journal

LANGUAGE: English

OTHER SOURCE(S) : CASREACT 102:24330

ED Entered STN: 26 Jan 1985

GI



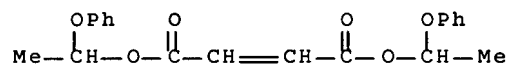
AB 4-RC6H4OCHMeCl (I, R = H, Cl, NHAc, NO₂) were prepared by treating 4-RC6H4OH with CH₂:CHOAc, elimination of HOAc, and hydrochlorination. I were used as carboxyl protective groups for penicillins and cephalosporins and were easily cleaved with 5% CF₃CO₂H-CH₂Cl₂. The penicillin II was simultaneously cleaved at the ester and silyl groups by treatment with HOAc-tetrahydrofuran-H₂O (4:2:1) at room temperature

IT 89753-66-2P

(preparation of)

RN 89753-66-2 HCAPLUS

CN 2-Butenedioic acid, bis(1-phenoxyethyl) ester (9CI) (CA INDEX NAME)

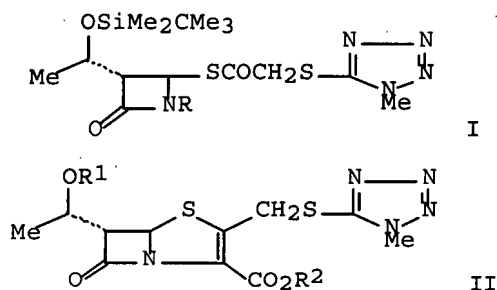


CC 26-5 (Biomolecules and Their Synthetic Analogs)
 Section cross-reference(s): 29
 IT 89753-65-1P 89753-66-2P 89753-68-4P 89753-69-5P
 89753-82-2P 89753-83-3P 89753-84-4P
 (preparation of)

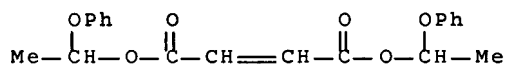
L9 ANSWER 41 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1984:191651 HCAPLUS Full-text
 DOCUMENT NUMBER: 100:191651
 TITLE: Easily cleavable carboxylic esters and their use
 in the synthesis of penems and other β -lactam
 antibiotics
 INVENTOR(S): Alpegiani, Marco; Bedeschi, Angelo; Perrone,
 Ettore; Gandolfi, Cermelo
 PATENT ASSIGNEE(S): Farmitalia Carlo Erba S.p.A., Italy
 SOURCE: Belg., 76 pp.
 CODEN: BEXXAL
 DOCUMENT TYPE: Patent
 LANGUAGE: French
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
BE 897183	A1	19831017	BE 1983-211097	19830630
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GB 2124614	A	19840222	GB 1983-14782	19830527
			<--	
GB 2124614	B	19851030		
DE 3323117	A1	19840105	DE 1983-3323117	19830627
			<--	
JP 59020286	A	19840201	JP 1983-117205	19830630
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PRIORITY APPLN. INFO.:			GB 1982-19052	A 19820701
			<--	

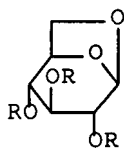
OTHER SOURCE(S): MARPAT 100:191651
 ED Entered STN: 08 Jun 1984
 GI



- AB The 1-phenoxyethyl group was used as a protective group in the synthesis of penems and related compds. Thus, $\text{PhOCH}_2\text{CH}_2$ was hydrochlorinated with HCl gas to give PhOCHMeCl which was esterified with L-(+)-tartaric acid and the resulting ester oxidized with $\text{Pb}(\text{OAc})_4$ to give $\text{HCOCO}_2\text{CHMeOPh}$. I ($\text{R} = \text{H}$) was treated with $\text{HCOCO}_2\text{CHMeOPh}$ to give I [$\text{R} = \text{CH}(\text{OH})\text{CO}_2\text{CHMeOPh}$] which was chlorinated and treated with PPh_3 to give I [$\text{R} = \text{C}(\text{:PPh}_3)\text{CO}_2\text{CHMeOPh}$]. Cyclization of the phosphorane gave II ($\text{R}_1 = \text{SiMe}_2\text{CMe}_3$, $\text{R}_2 = \text{CHMeOPh}$) which on desilylation, hydrolysis with aqueous oxalic acid, and treatment with NaHCO_3 gave II ($\text{R}_1 = \text{H}$, $\text{R}_2 = \text{Na}$).
- IT 89753-66-2P
(preparation and oxidation of)
- RN 89753-66-2 HCAPLUS
- CN 2-Butenedioic acid, bis(1-phenoxyethyl) ester. (9CI) (CA INDEX NAME)



- ICI. A61
- CC 26-5 (Biomolecules and Their Synthetic Analogs)
- IT 89753-66-2P
(preparation and oxidation of)
- L9 ANSWER 42 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
- ACCESSION NUMBER: 1980:181492 HCAPLUS Full-text
- DOCUMENT NUMBER: 92:181492
- TITLE: Synthesis and polymerization of unsaturated derivatives of hemiacetals of chloral, levoglucosan and its oligoethers
- AUTHOR(S): Apsite, B.; Pernikis, R.; Pundure, N.
- CORPORATE SOURCE: Inst. Khim. Drev., Riga, USSR
- SOURCE: Latvijas PSR Zinatnu Akademijas Vestis, Kimijas Serija (1979), (6), 708-12
CODEN: LZAKAM; ISSN: 0002-3248
- DOCUMENT TYPE: Journal
- LANGUAGE: Russian
- ED Entered STN: 12 May 1984
- GI



I, $\text{R} = \text{Cl}_3\text{CCHOH}$

II, $\text{R} = \left[\text{CH}_2\text{CH}(\text{OH}) \right]_n \text{CH}(\text{OH})\text{CCl}_3$

- AB Levoglucosan heated with Cl_3CCHO in an argon atmosphere 5 h at 65° gave 98% I. Analogous reactions of levoglucosan oligoethers gave II ($n = 1-12$).

Treatment of the latter with $\text{CH}_2:\text{CMeCOCl}$ gave 53-68% oligomers containing 3 double bonds per mol. Addnl. obtained were $\text{R}_1[\text{OCH}(\text{CCl}_3)\text{O}_2\text{CCR}_2:\text{CH}_2]_3$ (R_1 = levoglucosan residue, $\text{R}_2 = \text{H}, \text{Me}$). Rate consts. for polymerization of the unsatd. hemiacetals of hydroxypropylated levoglucosan were also determined

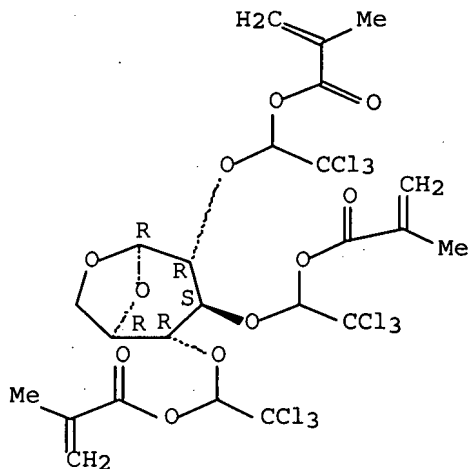
IT 65408-19-7P 73458-97-6P

(preparation of)

RN 65408-19-7 HCAPLUS

CN β -D-Glucopyranose, 1,6-anhydro-2,3,4-tris-O-[2,2,2-trichloro-1-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]- (9CI) (CA INDEX NAME)

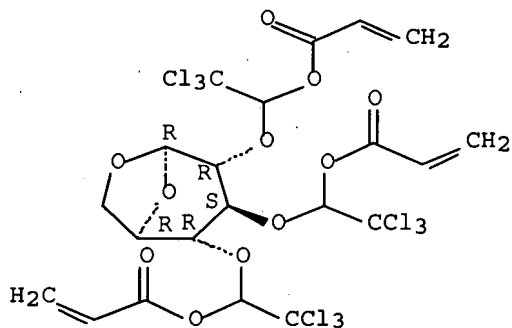
Absolute stereochemistry.



RN 73458-97-6 HCAPLUS

CN β -D-Glucopyranose, 1,6-anhydro-2,3,4-tris-O-[2,2,2-trichloro-1-[(1-oxo-2-propenyl)oxy]ethyl]- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



CC 33-2 (Carbohydrates)

Section cross-reference(s): 22

IT 65408-19-7P 73458-97-6P

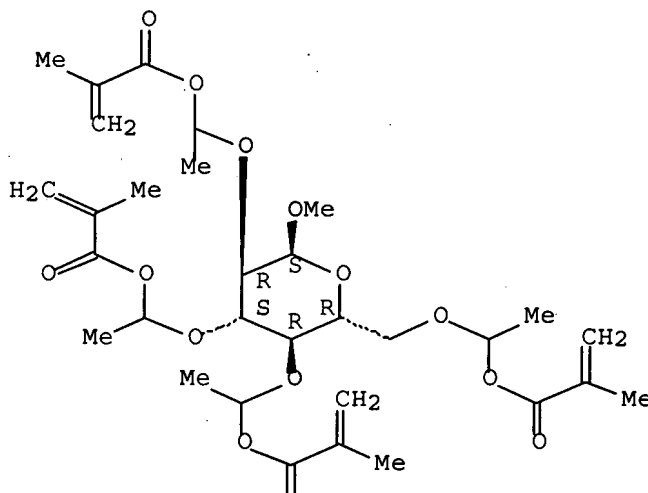
(preparation of)

L9 ANSWER 43 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1979:23423 HCAPLUS Full-text
 DOCUMENT NUMBER: 90:23423
 TITLE: Synthesis of hydrophilic polyesters of D-glucose
 AUTHOR(S): Lapenko, V. L.; Prokina, V. N.
 CORPORATE SOURCE: Voronezh. Gos. Univ., Voronezh, USSR
 SOURCE: Deposited Doc. (1976), VINITI 3401-76,
 12 pp. Avail.: VINITI
 DOCUMENT TYPE: Report
 LANGUAGE: Russian
 ED Entered STN: 12 May 1984
 AB Vinyl ethers of D-glucose and its Me glucoside were prepared by heating the monosaccharides with HC.tplbond.CH in aqueous dioxane in an autoclave 5 h at 160° and 12 atmospheric. Subsequent treatment with CH₂:CMeCO₂H or (CH₂:CMeCO)₂O gave hydrophilic polyesters. Addnl. obtained were polymethacrylates of D-glucose and its Me glucoside.
 IT 68115-89-9P
 (preparation of)
 RN 68115-89-9 HCAPLUS
 CN α-D-Glucopyranoside, methyl 2,3,4,6-tetrakis-O-[1-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]- (9CI) (CA INDEX NAME)

Absolute stereochemistry.

PAGE 1-A



PAGE 2-A

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CC 33-2 (Carbohydrates)
 Section cross-reference(s): 35
 IT 97-30-3DP, polyvinyl ethers 68091-36-1P 68103-40-2P 68103-41-3P
 68103-42-4P 68115-89-9P 68223-84-7P 68666-00-2P
 (preparation of)

BERNSHTEYN 10/537,120

L9 ANSWER 44 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1973:466391 HCAPLUS Full-text
 DOCUMENT NUMBER: 79:66391
 TITLE: Bronchodilating 4-hydroxy-5-phenoxyprymidines
 INVENTOR(S): Lipinski, Christopher A.; Stam, John G.;
 DeAngelis, Gerald G.; Hess, Hans J. E.
 PATENT ASSIGNEE(S): Pfizer Inc.
 SOURCE: Ger. Offen., 11 pp. Division of Ger. Offen.
 2,248,741.
 CODEN: GWXXBX
 DOCUMENT TYPE: Patent
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 4
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 2264374	A1	19730524	DE 1972-2264374	19721005
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DE 2264374	B2	19800807		
DE 2264374	C3	19810723		
GB 1377308	A	19741211	GB 1972-7748	19720218
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GB 1377720	A	19741218	GB 1973-50053	19720218
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SE 7505279	A	19750506	SE 1975-5279	19720925
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SE 397090	B	19771017		
SE 393376	B	19770509	SE 1972-12358	19720925
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AU 7247228	A	19740404	AU 1972-47228	19720928
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IL 40458	A	19760531	IL 1972-40458	19720928
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AT 320656	B	19750225	AT 1974-933	19721006
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AT 321308	B	19750325	AT 1972-8589	19721006
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FI 55503	C	19790810	FI 1972-2825	19721012
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FI 55503	B	19790430		
SU 498908	A3	19760105	SU 1972-1839308	19721013
			<--	
NO 136574	B	19770620	NO 1972-3686	19721013
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BE 790125	A1	19730416	BE 1972-1004478	19721016
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NL 7213959	A	19730502	NL 1972-13959	19721016
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NL 166470	B	19810316		
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FR 2157865	A1	19730608	FR 1972-36560	19721016
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JP 48052780	A	19730724	JP 1972-102799	19721016
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JP 53037870	B	19781012		
ZA 7207362	A	19731128	ZA 1972-7362	19721016
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CH 549579	A	19740531	CH 1974-1656	19721016

BERNSHTEYN 10/537,120

CH 555832	A	19741115	CH 1972-15078	19721016
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DK 131465	B	19750721	DK 1972-5100	19721016
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CA 980778	A1	19751230	CA 1972-153956	19721016
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PL 84634	B1	19760430	PL 1972-158297	19721016
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PL 89852	B1	19761231	PL 1972-174103	19721016
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ES 407730	A1	19760116	ES 1972-407730	19721018
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SU 505362	A3	19760228	SU 1974-2008490	19740326
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DK 134016	B	19760830	DK 1974-2949	19740531
			<--	
ES 436624	A1	19770201	ES 1975-436624	19750415
			<--	
NO 7603797	A	19730502	NO 1976-3797	19761108
			<--	
JP 54022995	B	19790810	JP 1978-13360	19780208
			<--	
JP 53116386	A	19781011		
FI 55504	C	19790810	FI 1978-1204	19780419
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FI 55504	B	19790430		
NL 8100488	A	19810601	NL 1981-488	19810202
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NL 172654	B	19830502		
NL 172654	C	19831003		
PRIORITY APPLN. INFO.:			US 1971-194006	A 19711029
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ED Entered STN: 12 May 1984

GI For diagram(s), see printed CA Issue.

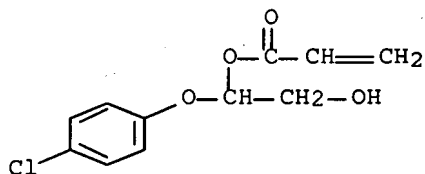
AB Ten title compds. (I; R = H, Cl, F, Me, MeO, or CO₂H; R₁ = H, 2- or 3-Cl, or 3-Me) were prepared from 5-phenoxythiouracils. Thus, thiourea, MeONa, and 4-ClC₆H₄OC(:CHONa)CO₂Et were refluxed in EtOH 14 hr to give 5-(4-chlorophenoxy)thiouracil (II). II was treated with Raney Ni in aqueous NaOH under N 1.5 hr at 60° to give I (R = Cl, R₁ = H). I had higher bronchodilating activity than theophylline.

IT 42310-29-2

(reaction with thiourea)

RN 42310-29-2 HCAPLUS

CN 2-Propenoic acid, 1-(4-chlorophenoxy)-2-hydroxyethyl ester (9CI) (CA INDEX NAME)



IC C07D
 CC 28-17 (Heterocyclic Compounds (More Than One Hetero Atom))
 IT 42310-29-2
 (reaction with thiourea)

L9 ANSWER 45 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1970:445708 HCAPLUS Full-text

DOCUMENT NUMBER: 73:45708

TITLE: Acylals and acetals based on dicyclohexylidene-D-glucose

AUTHOR(S): Mikhant'ev, B. I.; Lapenko, V. L.; Ponomarenko, E. Yu.

CORPORATE SOURCE: Voronezh. Gos. Univ., Voronezh, USSR

SOURCE: Zhurnal Obshchei Khimii (1970), 40(4), 911-14

CODEN: ZOKHA4; ISSN: 0044-460X

DOCUMENT TYPE: Journal

LANGUAGE: Russian

ED Entered STN: 12 May 1984

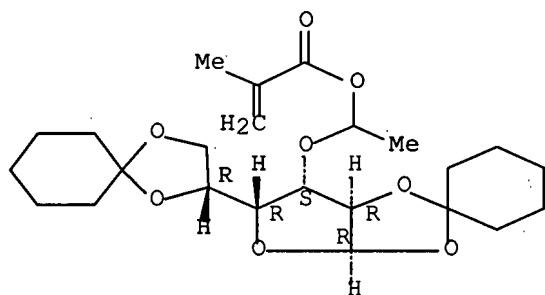
AB Keeping 0.01 mole 1,2:5,6-di-O-cyclohexylidene-3-O-vinyl-D-glucose (I) with 0.1 mole appropriate acid 21-8 hr at either 20-5° or 70° (only with AcOH and EtCO₂H) gave the appropriate acylals: 3-O-1-acyloxyethyl 1,2:5,6-di-O-cyclohexylidene-D-glucoses: formoxy, b₀.1 161-4°, d₂₀ 1.0115, n_{20D} 1.4910; acetoxy, b₀.1 160-3°, 1.1153, 1.3910; propionoxy, b₀.1 176-9°, 1.1072, 1.4880; isobutyroxy, b₀.1 180-2°, 1.1718, 1.4980; acryloxy, b₀.1 150-2°, 1.1888, 1.4960; and methacryloxy, b₀.1 195-8°, 1.1428, 1.4990. The yields were 51-68%. Hydrogenation over Raney Ni in EtOH converted the acryloxy and methacryloxy members to their saturated analogs. I in dry ROH in the presence of H₂SO₄ gave the corresponding acetal in 55-80% yield (alkoxy group shown): EtO, b₀.1 151-3°, 1.1788, 1.5093; PrO, b₀.1 152-5°, 1.0553, 1.5040; BuO, b₀.1 163-5°, 1.1510, 1.5058; and CH₂:CHCH₂O, b₀.1 140-3°, 1.1575, 1.5050. The Bu acetal was also prepared from BuOCH:CH₂ and 1,2:5,6-di-O-cyclohexylidene-D-glucose in the presence of H₂SO₄ in 65% yield in 10 hr.

IT 28867-42-7P 29024-86-0P
 (preparation of)

RN 28867-42-7 HCAPLUS

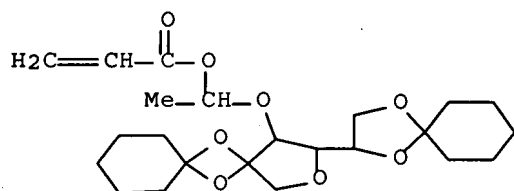
CN Glucofuranose, 1,2:5,6-di-O-cyclohexylidene-3-O-(1-hydroxyethyl)-, methacrylate, α-D- (8CI) (CA INDEX NAME)

Absolute stereochemistry.



RN 29024-86-0 HCAPLUS

CN Glucofuranose, 1,2:5,6-di-O-cyclohexylidene-3-O-(1-hydroxyethyl)-, acrylate, α -D- (8CI) (CA INDEX NAME)



CC 33 (Carbohydrates)

IT 182-00-3DP, Spiro[cyclohexane-1,2'-furo[2,3-d][1,3]dioxole], sugar derivs. 28867-40-5P 28867-41-6P 28867-42-7P 28867-43-8P 28867-44-9P 28867-45-0P 28867-46-1P 29024-84-8P 29024-85-9P 29024-86-0P (preparation of)

L9 ANSWER 46 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1955:73470 HCAPLUS Full-text

DOCUMENT NUMBER: 49:73470

ORIGINAL REFERENCE NO.: 49:13931b-e

TITLE: Chemical transformations of unsaturated and high molecular weight compounds. III. Copolymerization of methacrylic acid and its methyl ester with vinyl phenyl ether

AUTHOR(S): Shostakovskii, M. F.; Khomutov, A. M.

CORPORATE SOURCE: N. D. Zelinskii Inst. Org. Chem., Acad. Sci. U.S.S.R., Moscow

SOURCE: Izvestiya Akademii Nauk SSSR, Seriya Khimicheskaya (1954) 924-30

CODEN: IASKA6; ISSN: 0002-3353

DOCUMENT TYPE: Journal

LANGUAGE: Unavailable

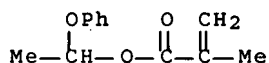
ED Entered STN: 22 Apr 2001

AB cf. C.A. 49, 9961a. Copolymerization of PhOCH:CH_2 with $\text{CH}_2:\text{CMeCO}_2\text{H}$ (I) and its Me ester (II) were run at 60° in the presence of 0.2% Bz_2O_2 ; a 1:1 ratio of the ether and II gave a copolymer soluble in 1:1 BuOH-PhOCH:CH_2 . At 1/3 ratio of II and PhOCH:CH_2 the copolymer was formed similarly and its solubility was similar to the above. As the proportion of PhOCH:CH_2 in the initial mixture was raised from 25% to 75%, the content of PhOCHCH_2 unit in

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the copolymer rose from 11.5 to 34.6%, but the yield of the copolymer declined from 76% to 10.56%. The absolute viscosity of the product declined from 0.021 to 0.0081, and relative viscosity from 2.89 to 1.09. Interaction of I and PhOCH:CH₂ in 3/1 ratio gave a 10% yield of product, containing 57.88% I units. At 1:1 proportion of reactants, the product contained 42% I units and had mol. weight 2265, while at 1:3 reactant proportion the product contained 53.5% I units. The liquid residue contained appreciable amts. of CH₂:CMeCO₂CHMeOPh. The results indicate that along with copolymerization side reactions take place which result in formation of acylals.

IT 255716-77-9P, Acetaldehyde, phenyl hemiacetal, methacrylate
(preparation of)
RN 255716-77-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-phenoxyethyl ester (9CI) (CA INDEX
NAME)



CC 10 (Organic Chemistry)
IT 255716-77-9P, Acetaldehyde, phenyl hemiacetal, methacrylate
255716-77-9P, Ethanol, 1-phenoxy-, methacrylate
(preparation of)

L9 ANSWER 47 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1954:3379 HCAPLUS Full-text

DOCUMENT NUMBER: 48:3379

ORIGINAL REFERENCE NO.: 48:580i,581a

TITLE: α-Butoxyethyl methacrylate

AUTHOR(S): Shostakovskii, M. F.; Gershtein, N. A.; Raskin,
Ya. L.; Ostroumova, L. E.

SOURCE: Akad. Nauk S.S.S.R., Inst. Org. Khim., Sintezy
Org. Soedinenii, Sbornik (1952), 2, 22-4

DOCUMENT TYPE: Journal

LANGUAGE: Unavailable

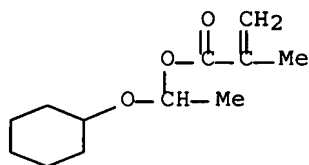
ED Entered STN: 22 Apr 2001

AB cf. C.A. 43, 3785i. Heating 25 g. BuOCH:CH₂ and 21.5 g. freshly distilled
CH₂:CMeCO₂H in sealed tube 5-5.5 hrs. on a steam bath gave on distillation in
N atmospheric 90% MeCH(OBu)O₂CCMe:CH₂, b₃₅ 99°, b₂₇ 86°, b₃₀ 89°, d₂₀ 0.9296,
n_{20D} 1.4256. Similarly were prepared: 84-5% MeCH(OEt)O₂CCMe:CH₂, b₂₄ 65°, b₃₄
73°, d₂₀ 0.9478, n_{20D} 1.4200; 78.5% MeCH(OCH₂Ph)O₂CCMe:CH₂, b₁₅ 83.7-4.0°, d₂₀
1.0367, n_{20D} 1.5008; 77.8% MeCH(OC₆H₁₁)O₂CCMe:CH₂, b₁₉ 112-12.5°, d₂₀ 0.9776,
n_{20D} 1.4560; the necessary vinyl cyclohexyl ether, b₂₃ 52-4°, d₂₀ 0.888, n_{20D}
1.4547.

IT 143556-62-1P, Ethanol, 1-(cyclohexyloxy)-, methacrylate
(preparation of)

RN 143556-62-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester (9CI) (CA
INDEX NAME)



CC 10 (Organic Chemistry)

IT 2182-55-0P, Ether, cyclohexyl vinyl 51920-52-6P, Ethanol, 1-ethoxy-, methacrylate 85997-75-7P, Ethanol, 1-butoxy-, methacrylate 143556-62-1P, Ethanol, 1-(cyclohexyloxy)-, methacrylate 408536-57-2P, Ethanol, 1-(benzyloxy)-, methacrylate (preparation of)

L9 ANSWER 48 OF 48 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 1953:28618 HCAPLUS Full-text

DOCUMENT NUMBER: 47:28618

ORIGINAL REFERENCE NO.: 47:4850a-e

TITLE: Synthesis and properties of 1-alkoxyethyl esters of unsaturated carboxylic acids (acylals)

AUTHOR(S): Shostakovskii, M. F.; Gershtein, N. A.; Raskin, Ya. L.; Ostroumova, L. E.

SOURCE: Izvestiya Akademii Nauk SSSR, Seriya Khimicheskaya (1952) 471-7

CODEN: IASKA6; ISSN: 0002-3353

DOCUMENT TYPE: Journal

LANGUAGE: Unavailable

ED Entered STN: 22 Apr 2001

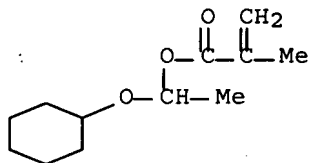
AB cf. C.A. 43, 3785.9. The syntheses of the acylals are based on addition of methacrylates to vinyl ethers. Heating 100 g. cyclohexanol and 10 g. KOH with C2H2 at 148-50° in an autoclave at 14-18 atmospheric pressure maintained by portionwise addition of C2H2 gave 68.6% vinyl cyclohexyl ether (I), b23 52-4°, b37 63°, b15 47.2-7.5°, nD20 1.4547, d420 0.888. Under the same conditions 210 g. cyclohexanol and 20 g. KOH gave 69.5% I; I hydrolyzes readily to AcH with 2% H2SO4. Similar conditions yield from 110 g. PhCH2OH and 11 g. KOH 62% vinyl benzyl ether (II), b22 81.5°, b24 82.5°, nD20 1.5185, d420 0.9711; PhCH2OH (80 g.) and 8 g. KOH gave 68%. Freshly distilled CH2:CMeCO2H (III), b. 160-1°, nD20 1.4113 (10.8 g.), and 20 g. II in a sealed tube gave in 4.5-5.0 hrs. at 100° 78.5% CH2:CMeCO2CHMe-OCH2Ph (IV), b14 82-2.2°. Addition with stirring of 0.05% by weight of 2% alc. H2SO4 to 5 g. III and 12.7 g. II caused a mild exothermic reaction with temperature rise to 50° in 1.25 hrs.; stirring 3 hrs. at 50° and letting stand overnight gave 77.6% IV, b15 83.7-4.0°, nD20 1.5008, n420 1.0367, hydrolyzed with formation of AcH by 2% H2SO4. Similarly, 8.6 g. III and 20.6 g. I in 5 hrs. at 100° gave 77.8% CH2:CMeCO2CHMe-OC6H11 (V), b20 114-15°; the 2nd method with 7 g. III and 19.4 g. I gave 79.1% V, b19 112-12.5°, b20 113.5-14.0°, nD20 1.4560, n420 0.9776. Similarly was obtained 93.3% CH2:CMeCO2CHMeOPh (by the 2nd method with H2SO4 catalyst after 2.5 hrs. at 60°), b15 98-9°, b20 129-30°, nD20 1.5030, n420 1.0561 (VI). The nature of the radical in the OR portion of these acylals affects the ease of hydrolysis. If R is aliphatic the cleavage occurs in few min. at room temperature with 2-5% H2SO4; with a cyclohexyl group it requires 25-30 min., with a PhCH2 group 1 hr., and with a Ph 3-5 hrs. at 100°.

IT 143556-62-1P, Ethanol, 1-(cyclohexyloxy)-, methacrylate 255716-77-9P, Acetaldehyde, phenyl hemiacetal, methacrylate (preparation of)

RN 143556-62-1 HCAPLUS

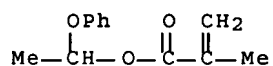
BERNSHTEYN 10/537,120

CN 2-Propenoic acid, 2-methyl-, 1-(cyclohexyloxy)ethyl ester (9CI) (CA INDEX NAME)



RN 255716-77-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-phenoxyethyl ester (9CI) (CA INDEX NAME)



CC 10 (Organic Chemistry)

IT 935-04-6P, Ether, benzyl vinyl 2182-55-0P, Ether, cyclohexyl vinyl
 7472-43-7P, Hexanoic acid, 6-benzoyl- 143556-62-1P, Ethanol,
 1-(cyclohexyloxy)-, methacrylate 255716-77-9P, Acetaldehyde,
 phenyl hemiacetal, methacrylate 255716-77-9P, Ethanol,
 1-phenoxy-, methacrylate 408536-57-2P, Ethanol, 1-(benzyloxy)-,
 methacrylate
 (preparation of)

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(FILE 'HOME' ENTERED AT 12:47:52 ON 18 SEP 2007)

FILE 'HCAPLUS' ENTERED AT 12:47:59 ON 18 SEP 2007

L1 1 SEA ABB=ON PLU=ON US20060160247/PN
SEL RN

FILE 'REGISTRY' ENTERED AT 12:48:24 ON 18 SEP 2007

L2 20 SEA ABB=ON PLU=ON (105-38-4/BI OR 274913-93-8/BI OR
474745-04-5/BI OR 500541-94-6/BI OR 52253-82-4/BI OR
6240-11-5/BI OR 79-41-4/BI OR 862474-62-2/BI OR 862474-63-3
/BI OR 862474-64-4/BI OR 862474-65-5/BI OR 862474-66-6/BI
OR 862474-67-7/BI OR 862474-68-8/BI OR 862474-69-9/BI OR
862474-70-2/BI OR 862474-71-3/BI OR 862474-72-4/BI OR
862474-73-5/BI OR 862474-74-6/BI)

L3 STR

L4 6 SEA SSS SAM L3
D SCA

L5 105 SEA SSS FUL L3

L6 10 SEA ABB=ON PLU=ON L2 AND L5
SAV L5 BER120/A

FILE 'HCAPLUS' ENTERED AT 13:07:09 ON 18 SEP 2007

L7 70 SEA ABB=ON PLU=ON L5

L8 63 SEA ABB=ON PLU=ON L7 AND (1840-2004)/PRY,AY,PY

L9 48 SEA ABB=ON PLU=ON L8 AND PREP/RL

L10 2 SEA ABB=ON PLU=ON L6

L11 1 SEA ABB=ON PLU=ON L9 AND